

Access DB# 208150

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Sin J. Lee Examiner #: 76060 Date: 11-29-2006
Art Unit: 1752 Phone Number 301-21333 Serial Number: 101673,332
Mail Box and Bldg/Room Location: 9C15 Results Format Preferred (circle): PAPER DISK E-MAIL
(Clem)

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Plz. See B.6. SCIENTIFIC REFERENCE BR
Sci & Tech Inf. Cntr

Inventors (please provide full names): _____
NOV 30 RECD

Earliest Priority Filing Date: _____ Pat. & T.M. Office
For Sequence Searches Only Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

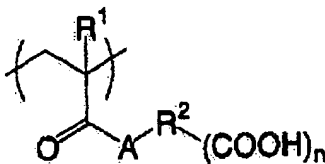
Please search for a polymer (in cl. #3)
having a repeating unit of formula (Z)
and a repeating unit having
an amide group

STAFF USE ONLY

	Type of Search	Vendors and cost where applicable
Searcher: <u>Ros</u>	NA Sequence (#) _____	STN <u>✓</u>
Searcher Phone #: _____	AA Sequence (#) _____	Dialog _____
Searcher Location: _____	Structure (#) <u>6</u>	Questel/Orbit _____
Date Searcher Picked Up: _____	Bibliographic _____	Dr. Link _____
Date Completed: <u>11/30/06</u>	Litigation _____	Lexis/Nexis _____
Searcher Prep & Review Time: <u>30</u>	Fulltext _____	Sequence Systems _____
Clerical Prep Time: _____	Patent Family _____	WWW/Internet _____
Online Time: <u>212</u>	Other _____	Other (specify) _____

Claim 3. (currently amended): ~~The A polymerizable composition according to claim 1, wherein the~~ comprising a binder polymer is a copolymer comprising at least the having a repeating unit represented by formula (I) and a repeating unit having a radical polymerizable group and/or a unit having an amide group; an infrared absorbent; a polymerization initiator; and a polymerizable compound:

Formula (I)



wherein R¹ represents a hydrogen atom or a methyl group; R² represents a linking group which includes one or more atoms selected from the group consisting of a carbon atom, a hydrogen atom, an oxygen atom, a nitrogen atom and a sulfur atom and has a number of atoms of 2 to 30; A represents an oxygen atom or -NR³- in which R³ represents a hydrogen atom or a monovalent hydrocarbon group having 1 to 10 carbon atoms; and n represents an integer of 1 to 5.

Claim 4. (original): The polymerizable composition according to claim 1, wherein a molecular weight of the binder polymer is 2,000 to 1,000,000.



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BIBDATASHEET

CONFIRMATION NO. 2251

Bib Data Sheet

SERIAL NUMBER 10/873,332	FILING DATE 09/30/2003 RULE	CLASS 430	GROUP ART UNIT 1752	ATTORNEY DOCKET NO. Q77298
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APPLICANTS

Atsushi Sugasaki, Shizuoka-ken, JAPAN;

Kazuto Kunita, Shizuoka-ken, JAPAN;

Kazuhiro Fujimaki, Shizuoka-ken, JAPAN;

** CONTINUING DATA *****

None. SJL

** FOREIGN APPLICATIONS *****

JAPAN 2002-287920 09/30/2002

JAPAN 2003-038288 02/17/2003

JAPAN 2003-100575 04/03/2003

SJL

IF REQUIRED, FOREIGN FILING LICENSE GRANTED

** 12/18/2003

Foreign Priority claimed <input checked="" type="checkbox"/> yes <input type="checkbox"/> no	STATE OR COUNTRY JAPAN	SHEETS DRAWING 1	TOTAL CLAIMS 20	INDEPENDENT CLAIMS 3
35 USC 119 (a-d) conditions met <input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> Met after Allowance				
Verified and Acknowledged	Examiner's Signature <i>[Signature]</i>	Initials SJL		

ADDRESS

23373

SUGHRUE MION, PLLC

2100 PENNSYLVANIA AVENUE, N.W.

SUITE 800

WASHINGTON, DC

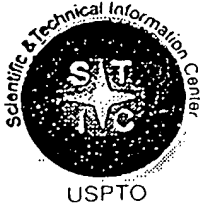
20037

TITLE

Polymerizable composition and planographic printing plate precursor

FILING FEE	FEES: Authority has been given in Paper	<input type="checkbox"/> All Fees
		<input type="checkbox"/> 1.16 Fees (Filing)
		<input type="checkbox"/> 1.17 Fees (Processing Ext. of

h e c e e e c e ce e b hee c b



STIC Search Results Feedback Form

EIC17000

Questions about the scope or the results of the search? Contact *the EIC searcher* or contact:

Kathleen Fuller, EIC 1700 Team Leader
571/272-2505 REMSEN 4B28

Voluntary Results Feedback Form

- I am an examiner in Workgroup: Example: 1713
➤ Relevant prior art **found**, search results used as follows:

- ☐ 102 rejection
- ☐ 103 rejection
- ☐ Cited as being of interest.
- ☐ Helped examiner better understand the invention.
- ☐ Helped examiner better understand the state of the art in their technology.

Types of relevant prior art found:

- ☐ Foreign Patent(s)
- ☐ Non-Patent Literature
(journal articles, conference proceedings, new product announcements etc.)

➤ Relevant prior art **not found**:

- ☐ Results verified the lack of relevant prior art (helped determine patentability).
- ☐ Results were not useful in determining patentability or understanding the invention.

Comments:

Drop off or send completed forms to EIC1700 REMSEN 4B28

=> d his full

(FILE 'HOME' ENTERED AT 13:25:05 ON 30 NOV 2006)

FILE 'HCAPLUS' ENTERED AT 13:25:21 ON 30 NOV 2006

E US20040072101/PN

L1 1 SEA ABB=ON PLU=ON US2004072101/PN
SEL RN

FILE 'REGISTRY' ENTERED AT 13:25:45 ON 30 NOV 2006

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24504-22-1/BI OR 253585-83-0/BI OR 377780-83-1/BI OR
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FILE 'HCAPLUS' ENTERED AT 13:25:55 ON 30 NOV 2006

L3 1 SEA ABB=ON PLU=ON L1 AND L2

FILE 'REGISTRY' ENTERED AT 14:08:33 ON 30 NOV 2006

L5 SCR 2043
L8 STRUCTURE
L9 50 SEA SSS SAM L8 AND L5
L10 33810 SEA SSS FUL L8 AND L5
SAV L10 LEE332/A
L11 STRUCTURE
L12 50 SEA SUB=L10 SSS SAM L11
L13 7674 SEA SUB=L10 SSS FUL L11
SAV L13 LEE332A/A
L18 STRUCTURE
L19 50 SEA SUB=L10 SSS SAM L18
L20 3305 SEA SUB=L10 SSS FUL L18
SAV L20 LEE33B/A
L21 10911 SEA ABB=ON PLU=ON L13 OR L20
L22 649 SEA ABB=ON PLU=ON L21 AND ?AMINO? AND ?AMIDE?
L23 10262 SEA ABB=ON PLU=ON L21 NOT L22
L24 726 SEA ABB=ON PLU=ON L23 AND ?AMIDE?
L25 1375 SEA ABB=ON PLU=ON L22 OR L24

FILE 'HCAPLUS' ENTERED AT 16:16:38 ON 30 NOV 2006

L26 873 SEA ABB=ON PLU=ON L25
L27 14 SEA ABB=ON PLU=ON L26 (L) (PLAN? OR PRINT?) (L)
?CURSOR?
L28 23 SEA ABB=ON PLU=ON L26 AND (PLAN? OR PRINT?) AND
?CURSOR?
L29 23 SEA ABB=ON PLU=ON L27 OR L28
L30 1 SEA ABB=ON PLU=ON L29 AND L3

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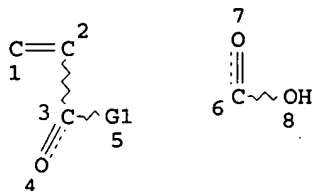
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=> d 129 que stat

L5 SCR 2043
L8 STR

VAR G1=O/N

NODE ATTRIBUTES:

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DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

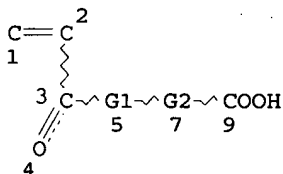
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STEREO ATTRIBUTES: NONE

L10 33810 SEA FILE=REGISTRY SSS FUL L8 AND L5

L11 STR

A@8



VAR G1=O/N

REP G2=(1-20) 8

NODE ATTRIBUTES:

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DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

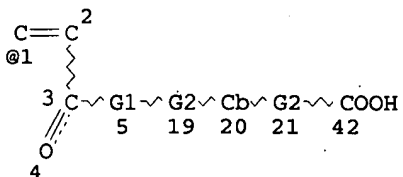
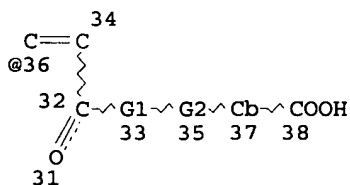
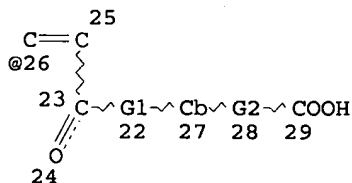
NUMBER OF NODES IS 8

STEREO ATTRIBUTES: NONE

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L18 STR

G3 8



VAR G1=O/N
REP G2=(0-14) A
VAR G3=1/26/36
NODE ATTRIBUTES:
DEFAULT MLEVEL IS ATOM
DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
RING(S) ARE ISOLATED OR EMBEDDED
NUMBER OF NODES IS 26

STEREO ATTRIBUTES: NONE

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L22 649 SEA FILE=REGISTRY ABB=ON PLU=ON L21 AND ?AMINO? AND
?AMIDE?
L23 10262 SEA FILE=REGISTRY ABB=ON PLU=ON L21 NOT L22
L24 726 SEA FILE=REGISTRY ABB=ON PLU=ON L23 AND ?AMIDE?
L25 1375 SEA FILE=REGISTRY ABB=ON PLU=ON L22 OR L24
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L28 23 SEA FILE=HCAPLUS ABB=ON PLU=ON L26 AND (PLAN? OR
PRINT?) AND ?CURSOR?
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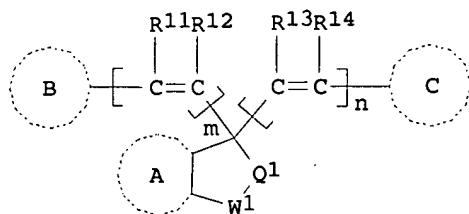
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=> d l29 1-23 ibib abs hitstr hitind

L29 ANSWER 1 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2006:1035056 HCAPLUS
DOCUMENT NUMBER: 145:407653
TITLE: IR laser-sensitive lithographic printing
plate precursors
INVENTOR(S): Nagashima, Akiya
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 43pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006267290	A2	20061005	JP 2005-82767	200503 22
PRIORITY APPLN. INFO.:				JP 2005-82767 200503 22

GI



I

AB The title **printing plate precursor** has a pos.-working image-forming layer on a support, wherein the image-forming layer contains a urea bond-containing polymer and a acid-sensitive coloring compound I (ring A-B = 1-3 consisting ring aromatic hydrocarbon, aromatic heterocyclic ring unit; W1 = carbonyl, thiocarbonyl, -C(R15)=N-; R15 = H, hydrocarbon; Q1 = O, S, imino; R11-14 = H, hydrocarbon; m,n = 0, 1). The **printing plate precursor** shows good chemical resistance and high dissoln. discrimination for the development.

IT 309967-76-8P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(polymer in image-forming layer of lithog. **printing plate precursor**)

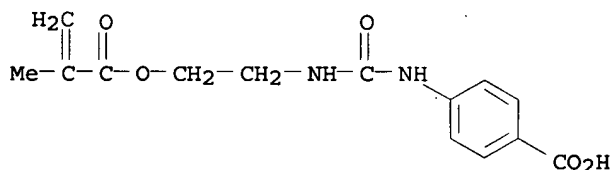
RN 309967-76-8 HCAPLUS

CN Benzoic acid, 4-[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]carbonyl]amino]-, polymer with 2-methyl-2-propenamide and 1-phenyl-1H-pyrrole-2,5-dione (9CI) (CA INDEX NAME)

CM 1

CRN 154868-64-1

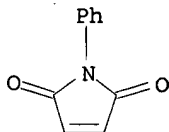
CMF C14 H16 N2 O5



CM 2

CRN 941-69-5

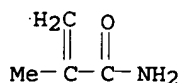
CMF C10 H7 N O2



CM 3

CRN 79-39-0

CMF C4 H7 N O



CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35

ST IR lithog printing plate precursor polymer coloring

IT Lithographic plates
(IR laser-sensitive lithog. printing plate precursors)

IT Photoimaging materials
(photopolymerizable; IR laser-sensitive lithog. printing plate precursors)

IT 1552-42-7 70516-48-2 200274-66-4 220271-49-8 220271-52-3 882037-19-6
RL: TEM (Technical or engineered material use); USES (Uses)
(acid-sensitive coloring compound in image-forming layer of lithog. printing plate precursor)

IT 123-30-8, 4-Aminophenol 150-13-0, 4-Aminobenzoic acid 30674-80-7, 2-(Methacryloxy)ethyl isocyanate
RL: RCT (Reactant); RACT (Reactant or reagent)
(polymer in image-forming layer of lithog. printing plate precursor)

IT 154868-64-1P, 2-[N'-(4-Carboxyphenyl)ureido]ethyl methacrylate 184348-63-8P, 2-[N'-(4-Hydroxyphenyl)ureido]ethyl methacrylate
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(polymer in image-forming layer of lithog. printing plate precursor)

IT 184348-67-2P 263716-62-7P 309967-75-7P 309967-76-8P 467242-74-6P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polymer in image-forming layer of lithog. printing plate precursor)

L29 ANSWER 2 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2006:1004763 HCAPLUS
DOCUMENT NUMBER: 145:386557
TITLE: IR sensitive positive planographic printing plate precursor
INVENTOR(S): Nagashima, Akira
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 44pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1705004	A1	20060927	EP 2006-5624	20060320
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, BA, HR, IS, YU				
JP 2006267293	A2	20061005	JP 2005-82770	200503

PRIORITY APPLN. INFO.:

JP 2005-82770

22
A
200503
22

AB The **planog. printing plate precursor** of the invention contains a substrate and a pos. recording layer prepared on the substrate, and the recording layer contains (A) a polymer having a urea bond in a side chain, (B) a photothermal conversion agent, and (C) an amino compound having a methylol group or an alkoxymethyl group, and its solubility in an alkaline developing solution is improved by light-exposure or heating.

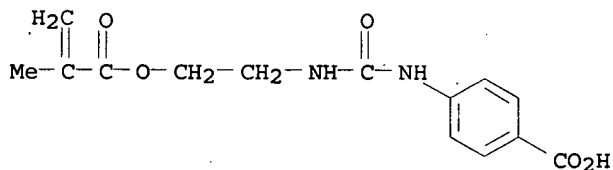
IT **309967-77-9P**, 2-[N'-(4-Carboxyphenyl)ureido]ethyl methacrylate-methyl methacrylate-methacrylamide copolymer
309967-78-0P, 2-[N'-(4-Carboxyphenyl)ureido]ethyl methacrylate-acrylonitrile-methacrylamide copolymer
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (IR sensitive pos. **planog. printing plate precursor**)

RN 309967-77-9 HCAPLUS

CN Benzoic acid, 4-[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]carbonyl]amino]-, polymer with methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

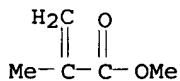
CM 1

CRN 154868-64-1
 CMF C14 H16 N2 O5



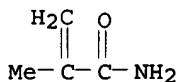
CM 2

CRN 80-62-6
 CMF C5 H8 O2



CM 3

CRN 79-39-0
 CMF C4 H7 N O

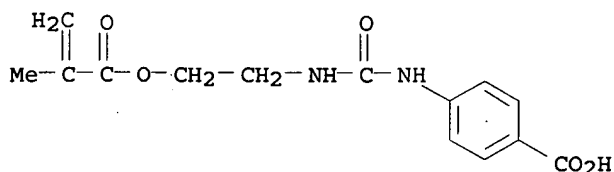


RN 309967-78-0 HCAPLUS

CN Benzoic acid, 4-[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]carbonyl]amino]-, polymer with 2-methyl-2-propenamide and 2-propenenitrile (9CI) (CA INDEX NAME)

CM 1

CRN 154868-64-1
CMF C14 H16 N2 O5



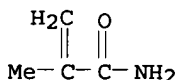
CM 2

CRN 107-13-1
CMF C3 H3 N



CM 3

CRN 79-39-0
CMF C4 H7 N O



CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST **planog printing plate precursor** pos
recording layer urea bond; photothermal conversion agent IR
printing plate

IT **Printing plates**
(**planog.**; IR sensitive pos. **planog.**
printing plate precursor)

IT 103-71-9, Phenyl isocyanate, reactions 123-30-8, 4-Aminophenol
150-13-0, 4-Aminobenzoic acid 30674-80-7

RL: RCT (Reactant); RACT (Reactant or reagent)

(IR sensitive pos. **planog. printing plate precursor**)

IT 2298-29-5P, 4-(N'-Phenylureido)phenol 154868-64-1P,
2-[N'-(4-Carboxyphenyl)ureido]ethyl methacrylate 184348-63-8P,
2-[N'-(4-Hydroxyphenyl)ureido]ethyl methacrylate

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation);
RACT (Reactant or reagent)

(IR sensitive pos. **planog. printing plate precursor**)

IT 184348-64-9P, Formaldehyde-4-(N'-phenylureido)phenol polymer
184348-67-2P, N-Phenylmaleimide-2-[N'-(4-hydroxyphenyl)ureido]ethyl
methacrylate copolymer 184348-69-4P, 2-[N'-(4-Carboxyphenyl)ureido]ethyl methacrylate-N-phenylmaleimide-
methacrylamide copolymer 309967-75-7P, 2-[N'-(4-

Carboxyphenyl)ureido]ethyl methacrylate-N-Phenylmaleimide copolymer
 309967-77-9P, 2-[N'-(4-Carboxyphenyl)ureido]ethyl
 methacrylate-methyl methacrylate-methacrylamide copolymer
 309967-78-0P, 2-[N'-(4-Carboxyphenyl)ureido]ethyl
 methacrylate-acrylonitrile-methacrylamide copolymer

RL: SPN (Synthetic preparation); TEM (Technical or engineered
 material use); PREP (Preparation); USES (Uses)

(IR sensitive pos. planog. printing plate
 precursor)

IT 2390-59-2, Ethyl violet 3089-11-0 13439-97-9 27029-76-1
 134127-48-3 220227-02-1 880517-75-9 880517-76-0 903547-47-7
 903547-48-8 911100-88-4, Defensa F 780F

RL: TEM (Technical or engineered material use); USES (Uses)

(IR sensitive pos. planog. printing plate
 precursor)

REFERENCE COUNT: 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR
 THIS RECORD. ALL CITATIONS AVAILABLE IN
 THE RE FORMAT

L29 ANSWER 3 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2006:890083 HCAPLUS

DOCUMENT NUMBER: 145:302827

TITLE: Planographic printing plate
 precursor

INVENTOR(S): Kakino, Ryuki

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Eur. Pat. Appl., 57pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1695821	A2	20060830	EP 2006-3687	20060223
EP 1695821	A3	20061004		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, BA, HR, IS, YU				
JP 2006235390	A2	20060907	JP 2005-51837	20050225
US 2006194146	A1	20060831	US 2006-354016	20060215
PRIORITY APPLN. INFO.:				20050225
				A
				20050225

AB The planog. printing plate precursor of the present invention comprises a substrate, and a recording layer provided on the substrate, the recording layer comprises a polymer compound having a partial structure of (1) silicon-oxygen bonds and (2) alkali-soluble groups. This planog. printing plate precursor provides excellent inking property on the image portion, and suppresses the generation of deposits such as sludge in a developing solution during the plate-making process.

IT 908002-00-6

RL: TEM (Technical or engineered material use); USES (Uses)

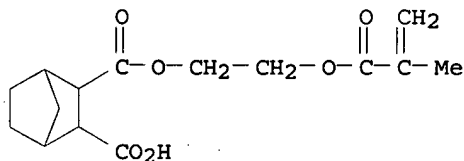
(planog. printing plate precursor
 containing acrylic siloxane polymers)

RN 908002-00-6 HCAPLUS
 CN Bicyclo[2.2.1]heptane-2,3-dicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with cyclohexyl 2-methyl-2-propenoate, 2-methyl-N-(1-methylethyl)-2-propenamide and [3,3,3-trimethyl-1,1-bis[(trimethylsilyl)oxy]disiloxanyl)methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 214961-25-8

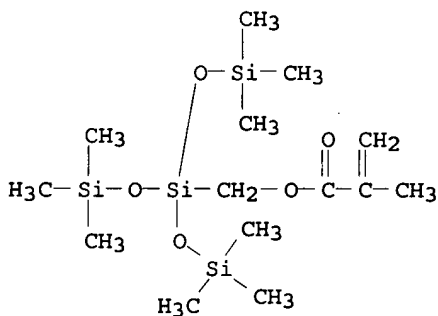
CMF C15 H20 O6



CM 2

CRN 74681-63-3

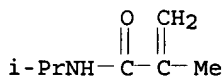
CMF C14 H34 O5 Si4



CM 3

CRN 13749-61-6

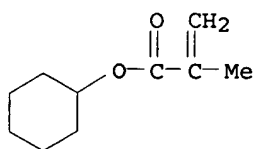
CMF C7 H13 N O



CM 4

CRN 101-43-9

CMF C10 H16 O2



CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST **planog printing plate precursor**
polysiloxane acrylic graft

IT Polysiloxanes, preparation
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylic, graft; **planog. printing plate precursor** containing acrylic siloxane polymers)

IT Polysiloxanes, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(carboxy-containing; **planog. printing plate precursor** containing acrylic siloxane polymers)

IT **Printing plates**
(**planog.**; **planog. printing plate precursor** containing acrylic siloxane polymers)

IT 468055-02-9P 908001-77-4P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(**planog. printing plate precursor** containing acrylic siloxane polymers)

IT 908001-78-5 908001-80-9 908001-83-2 908001-85-4 908001-86-5
908001-87-6 908001-88-7 908001-89-8 908001-90-1 908001-91-2
908001-93-4 908001-95-6 908001-97-8 908001-99-0
908002-00-6 908002-02-8 908002-04-0 908002-06-2
908002-08-4 908002-11-9 908002-14-2 908002-17-5 908002-19-7
RL: TEM (Technical or engineered material use); USES (Uses)
(**planog. printing plate precursor** containing acrylic siloxane polymers)

L29 ANSWER 4 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2006:362968 HCAPLUS

DOCUMENT NUMBER: 144:422717

TITLE: Lithographic **printing plate precursors** and method for **printing** using **printing plate** therefrom

INVENTOR(S): Yamazaki, Sumiaki; Endo, Akihiro

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 66 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006102947	A2	20060420	JP 2004-288262	20040930
PRIORITY APPLN. INFO.:			JP 2004-288262	20040930

AB The title **printing plate precursor** has an

undercoat layer and a laser beam-sensitive photopolymerizable layer on a hydrophilic layer, wherein the undercoat layer has $\geq 5^\circ$ increased contact angle after laser beam irradiation. The **printing plate precursor** shows good development characteristics and provides **printing plates** of high resolution and high **printing durability**.

IT 883744-43-2

RL: TEM (Technical or engineered material use); USES (Uses)
(undercoat layer of lithog. **printing plate precursors**)

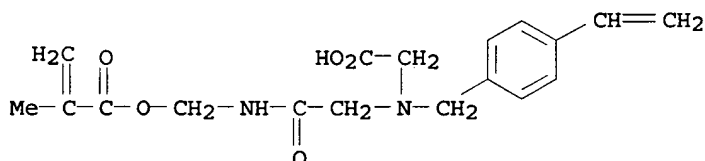
RN 883744-43-2 HCAPLUS

CN Glycine, N-(carboxymethyl)-N-[(4-ethenylphenyl)methyl]-, polymer with [[[(carboxymethyl)[(4-ethenylphenyl)methyl]amino]acetyl]amino]methyl 2-methyl-2-propenoate and N-(1-methylethyl)-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 883744-42-1

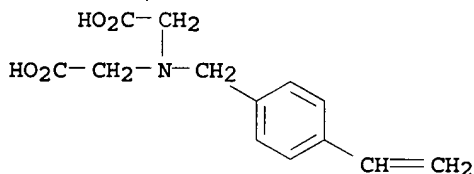
CMF C18 H22 N2 O5



CM 2

CRN 46917-20-8

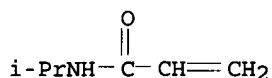
CMF C13 H15 N O4



CM 3

CRN 2210-25-5

CMF C6 H11 N O



CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35

ST lithog **printing plate precursor** contact angle

IT Lithographic plates

(lithog. **printing plate precursors** and method
for **printing** using **printing plate** therefrom)

IT 883744-35-2 883744-36-3 883744-37-4 883744-38-5 883744-39-6

883744-41-0 883744-43-2 883744-44-3 883744-45-4
 883744-46-5 883744-47-6 883744-48-7 883744-50-1 883744-51-2
 RL: TEM (Technical or engineered material use); USES (Uses)
 (undercoat layer of lithog. printing plate
 precursors)

L29 ANSWER 5 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2006:164437 HCAPLUS

DOCUMENT NUMBER: 144:263618

TITLE: Planographic printing plate
 precursor

INVENTOR(S): Kakino, Ryuki; Nakamura, Ippei; Kawauchi, Ikuro

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Eur. Pat. Appl., 73 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

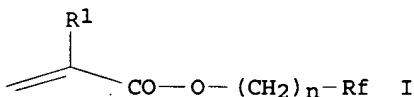
LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1627734	A2	20060222	EP 2005-17753	20050816
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, BA, HR, IS, YU				
JP 2006053487	A2	20060223	JP 2004-236767	20040816
CN 1737682	A	20060222	CN 2005-10091689	20050816
US 2006057493	A1	20060316	US 2005-204229	20050816
JP 2006106723	A2	20060420	JP 2005-261107	20050816
PRIORITY APPLN. INFO.:			JP 2004-236767	A
			JP 2004-261593	A

GI



AB The pos.-type planog. printing plate precursor of the invention comprises a support and a recording layer provided on the support, wherein the recording layer contains: a polymer compound having (a) a monomer I (Rf = substituent containing a fluoroalkyl group or a perfluoroalkyl group having 9 or more fluorine atoms; n = 1 or 2; R1 = H, Me group), (b) a monomer having an aliphatic group having 7 or more carbon atoms and having a

bridge bond, and (c) a monomer having an acid group as a copolymn. component; and an IR-ray absorbing agent. The pos.-type planog. printing plate precursor of the invention achieves both excellent developability and excellent inking property, as well as better image-forming property and a clear image.

IT 876944-80-8 876944-95-5 876945-17-4

876945-19-6 876945-21-0 876945-29-8

RL: PRP (Properties); TEM (Technical or engineered material use);

USES (Uses)

(planog. printing plate precursor containing)

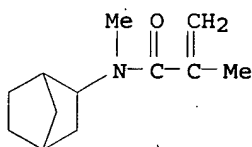
RN 876944-80-8 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-bicyclo[2.2.1]hept-2-yl-N,2-dimethyl-2-propenamide and 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 876944-79-5

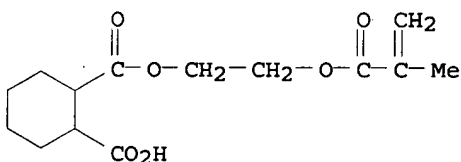
CMF C12 H19 N O



CM 2

CRN 51252-88-1

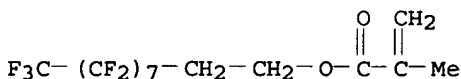
CMF C14 H20 O6



CM 3

CRN 1996-88-9

CMF C14 H9 F17 O2

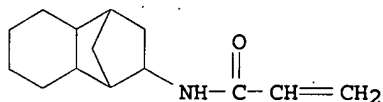


RN 876944-95-5 HCAPLUS

CN 1,1-Cyclopentanediadicetic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-(decahydro-1,4-methanonaphthalen-2-yl)-2-propenamide and 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

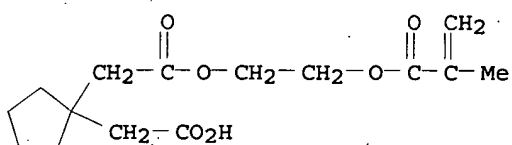
CM 1

CRN 876944-94-4
CMF C14 H21 N O



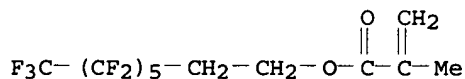
CM 2

CRN 393546-18-4
CMF C15 H22 O6



CM 3

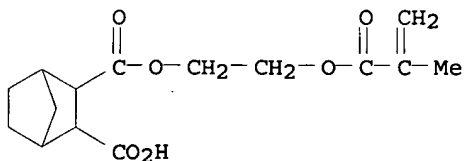
CRN 2144-53-8
CMF C12 H9 F13 O2



RN 876945-17-4 HCAPLUS
CN Bicyclo[2.2.1]heptane-2,3-dicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8-dodecafluorooctyl 2-methyl-2-propenoate and 2-methyl-N-(octahydro-4,7-methano-1H-inden-5-yl)-2-propenamide (9CI) (CA INDEX NAME)

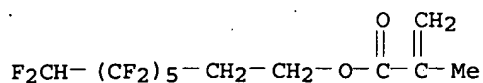
CM 1

CRN 214961-25-8
CMF C15 H20 O6



CM 2

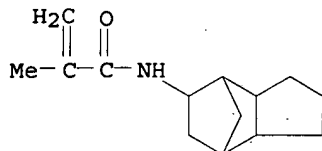
CRN 107760-97-4
CMF C12 H10 F12 O2



CM 3

CRN 14415-19-1

CMF C14 H21 N O



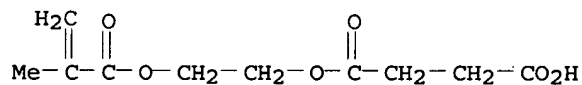
RN 876945-19-6 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-(decahydro-1,4:5,8-dimethanonaphthalen-2-yl)-2-methyl-2-propenamide, dodecyl 2-methyl-2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

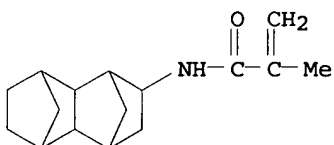
CMF C10 H14 O6



CM 2

CRN 15187-51-6

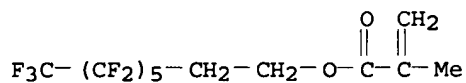
CMF C16 H23 N O



CM 3

CRN 2144-53-8

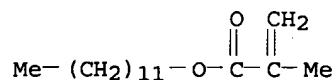
CMF C12 H9 F13 O2



CM 4

CRN 142-90-5

CMF C16 H30 O2



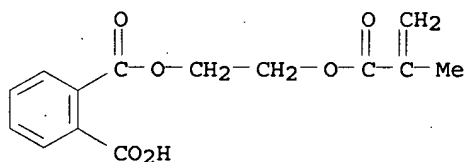
RN 876945-21-0 HCAPLUS

CN 1,2-Benzenedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 2-ethylhexyl 2-methyl-2-propenoate, 2-methyl-N-(octahydro-4,7-methano-1H-inden-5-yl)-2-propenamide and 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 27697-00-3

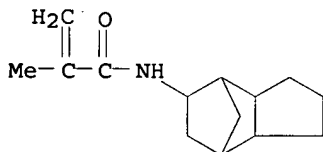
CMF C14 H14 O6



CM 2

CRN 14415-19-1

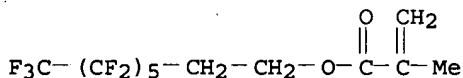
CMF C14 H21 N O



CM 3

CRN 2144-53-8

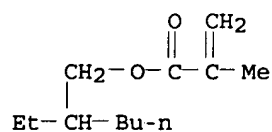
CMF C12 H9 F13 O2



CM 4

CRN 688-84-6

CMF C12 H22 O2



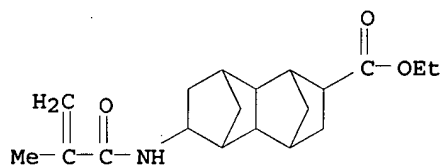
RN 876945-29-8 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with ethyl decahydro-6-[(2-methyl-1-oxo-2-propenyl)amino]-1,4:5,8-dimethanonaphthalene-2-carboxylate, 2-methyl-N-tricyclo[3.3.1.1^{3,7}]dec-2-yl-2-propenamide and 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 876945-28-7

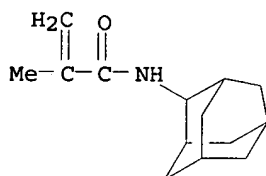
CMF C19 H27 N O3



CM 2

CRN 134110-07-9

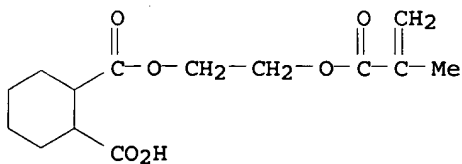
CMF C14 H21 N O



CM 3

CRN 51252-88-1

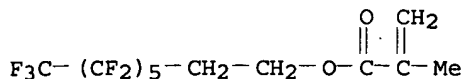
CMF C14 H20 O6



CM 4

CRN 2144-53-8

CMF C12 H9 F13 O2



CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 35, 38

ST **planog printing plate precursor**

IT **Printing plates**

(**planog.**; **planog. printing plate precursor**)

IT 876945-40-3

RL: PRP (Properties); TEM (Technical or engineered material use);
USES (Uses)

(**lanog. printing plate precursor containing**)

IT 817203-49-9 876315-63-8 876944-76-2 876944-77-3 876944-78-4
876944-80-8 876944-81-9 876944-83-1 876944-84-2
 876944-85-3 876944-86-4 876944-87-5 876944-88-6 876944-90-0
 876944-92-2 **876944-95-5** 876944-98-8 876945-00-5
 876945-02-7 876945-05-0 876945-07-2 876945-10-7 876945-12-9
 876945-14-1 876945-15-2 **876945-17-4 876945-19-6**
876945-21-0 876945-23-2 876945-25-4 876945-26-5
876945-29-8 876945-31-2 876945-33-4 876945-34-5
 876945-35-6 876945-37-8 876945-39-0 876945-42-5 876945-44-7
 876945-46-9 876945-47-0 876945-50-5 876945-52-7 876945-54-9
 876945-57-2 876945-59-4 876945-61-8 876945-62-9 876945-66-3

RL: PRP (Properties); TEM (Technical or engineered material use);
USES (Uses)

(**planog. printing plate precursor containing**)

L29 ANSWER 6 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2005:303261 HCAPLUS

DOCUMENT NUMBER: 142:382218

TITLE: Lithographic **printing plate precursor** and lithographic **printing method**

INVENTOR(S): Makino, Naonori; Inno, Toshifumi; Yamasaki, Sumiaki

PATENT ASSIGNEE(S): Japan

SOURCE: U.S. Pat. Appl. Publ., 35 pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005074692	A1	20050407	US 2004-951700	20040929
JP 2005125749	A2	20050519	JP 2004-265735	20040913
EP 1520694	A2	20050406	EP 2004-23373	20040930
EP 1520694	A3	20051207		

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC,
PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU,

PL, SK, HR
PRIORITY APPLN. INFO.:

JP 2003-339391

A

200309
30

AB A lithog. printing plate precursor comprises: a support; and at least one layer comprising an image-recording layer, the image-recording layer comprising (A) an IR absorber, (B) a polymerization initiator, (C) a polymerizable compound, and (D) a binder polymer, wherein the image recording layer is capable of being removed with at least one of a printing ink and a fountain solution, wherein at least one of said at least one layer comprises a copolymer having (a1) a unit comprising at least one ethylenically unsatd. bond, and (a2) a unit comprising at least one functional group interacting with a surface of the support. And a lithog. printing method in which the lithog. printing plate precursor is used. The copolymer preferably has a hydrophilic segment. The copolymer preferably is contained in an undercoat layer formed between the support and the image-recording layer.

IT 849467-49-8P

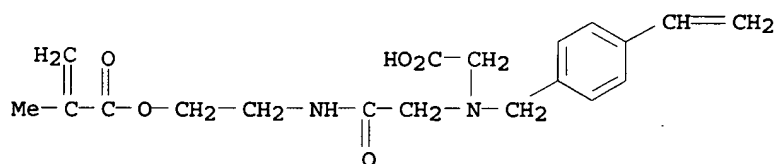
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(lithog. printing plate precursor containing)

RN 849467-49-8 HCAPLUS

CN Glycine, N-(carboxymethyl)-N-[(4-ethenylphenyl)methyl]-, polymer with 2-[[[(carboxymethyl)[(4-ethenylphenyl)methyl]amino]acetyl]amino]ethyl 2-methyl-2-propenoate and N-(1-methylethyl)-2-propenamide (9CI) (CA INDEX NAME)

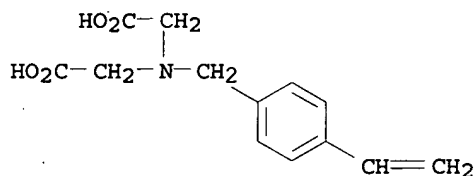
CM 1

CRN 849467-47-6
CMF C19 H24 N2 O5



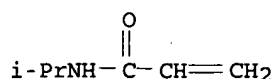
CM 2

CRN 46917-20-8
CMF C13 H15 N O4



CM 3

CRN 2210-25-5
CMF C6 H11 N O



IC ICM G03C0001-76
 INCL 430270100
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and
 Other Reprographic Processes)
 Section cross-reference(s): 35, 38
 ST lithog printing plate precursor
 IT Optical materials
 (IR absorbers; lithog. printing plate precursor
 and lithog. printing method)
 IT IR materials
 (absorbers; lithog. printing plate precursor
 and lithog. printing method)
 IT Lithographic plates
 (lithog. printing plate precursor and lithog.
 printing method)
 IT 83176-82-3P 93441-11-3P 194715-96-3P 849467-38-5P
 849467-39-6P 849467-40-9P 849467-41-0P 849467-43-2P
 849467-44-3P 849467-45-4P 849467-46-5P 849467-48-7P
 849467-49-8P 849467-50-1P 849467-51-2P 849467-52-3P
 849467-53-4P 849467-54-5P 849467-55-6P
 RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or
 engineered material use); PREP (Preparation); USES (Uses)
 (lithog. printing plate precursor containing)

L29 ANSWER 7 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 2005:302459 HCAPLUS
 DOCUMENT NUMBER: 142:363846
 TITLE: Photopolymerizable photoimaging resin
 compositions for image-forming layer of
 lithographic printing plates
 INVENTOR(S): Kunita, Kazuto
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 101 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005091618	A2	20050407	JP 2003-323411	20030916
PRIORITY APPLN. INFO.:				20030916

AB The composition contains an alkali-solubilizable radically-crosslinkable
 polymers, wherein the polymer has radically crosslinking
 alkali-solubilizable groups and unsatd. double bonds in the side
 chain. The composition shows high sensitivity and good storageability
 and provides good developing characteristics.

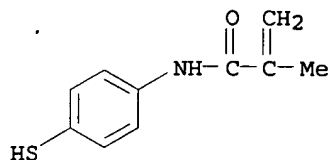
IT 849240-85-3 849240-88-6 849240-91-1
 849240-94-4 849241-04-9
 RL: TEM (Technical or engineered material use); USES (Uses)
 (resin in photopolymerizable photoimaging resin compns.)
 RN 849240-85-3 HCAPLUS
 CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-

propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl
bis(2-methyl-2-propenoate), N-(4-mercaptophenyl)-2-methyl-2-
propenamide and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 286425-98-7

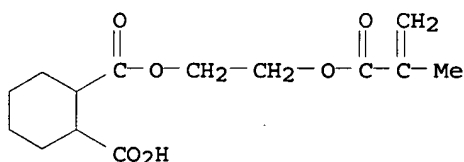
CMF C10 H11 N O S



CM 2

CRN 51252-88-1

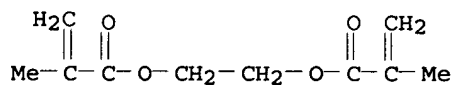
CMF C14 H20 O6



CM 3

CRN 97-90-5

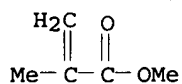
CMF C10 H14 O4



CM 4

CRN 80-62-6

CMF C5 H8 O2



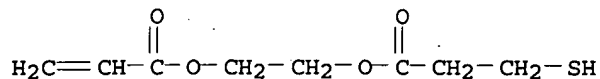
RN 849240-88-6 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate),
2-(3-mercapto-1-oxopropoxy)ethyl 2-propenoate and
2-methyl-N-phenyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 150752-87-7

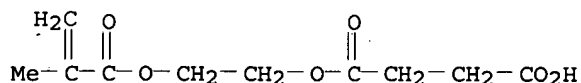
CMF C8 H12 O4 S



CM 2

CRN 20882-04-6

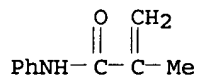
CMF C10 H14 O6



CM 3

CRN 1611-83-2

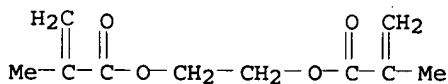
CMF C10 H11 N O



CM 4

CRN 97-90-5

CMF C10 H14 O4



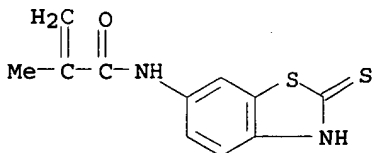
RN 849240-91-1 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-(2,3-dihydro-2-thioxo-6-benzothiazolyl)-2-methyl-2-propenamide, N-(4-hydroxyphenyl)-2-methyl-2-propenamide, methyl 2-methyl-2-propenoate and 2-[(2-methyl-1-oxo-2-propenyl)amino]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 849240-90-0

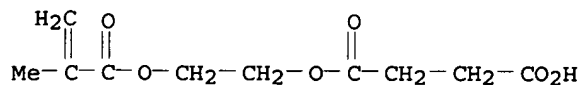
CMF C11 H10 N2 O S2



CM 2

CRN 20882-04-6

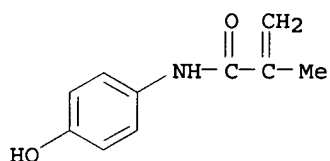
CMF C10 H14 O6



CM 3

CRN 19243-95-9

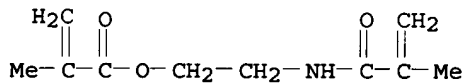
CMF C10 H11 N O2



CM 4

CRN 6206-58-2

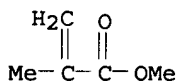
CMF C10 H15 N O3



CM 5

CRN 80-62-6

CMF C5 H8 O2



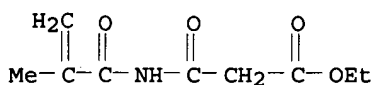
RN 849240-94-4 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), ethyl 3-[(2-methyl-1-oxo-2-propenyl)amino]-3-oxopropanoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 849240-93-3

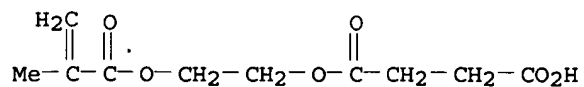
CMF C9 H13 N O4



CM 2

CRN 20882-04-6

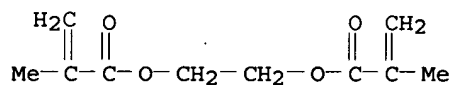
CMF C10 H14 O6



CM 3

CRN 97-90-5

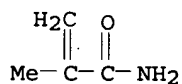
CMF C10 H14 O4



CM 4

CRN 79-39-0

CMF C4 H7 N O



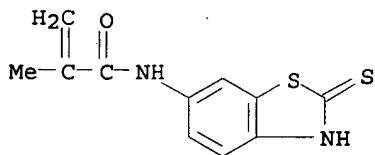
RN 849241-04-9 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-(2,3-dihydro-2-thioxo-6-benzothiazolyl)-2-methyl-2-propenamide, 1,2-ethanediyl bis(2-methyl-2-propenoate) and methyl 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

CM 1

CRN 849240-90-0

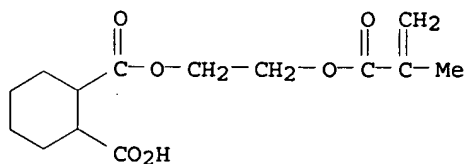
CMF C11 H10 N2 O S2



CM 2

CRN 51252-88-1

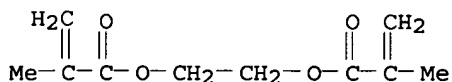
CMF C14 H20 O6



CM 3

CRN 97-90-5

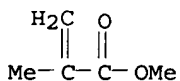
CMF C10 H14 O4



CM 4

CRN 80-62-6

CMF C5 H8 O2



IC ICM G03F0007-038

ICS C08F0290-08

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 37

ST photopolymerizable photoimaging compn resin lithog printing plate

IT Photoimaging materials

(photopolymerizable; photopolymerizable photoimaging resin compns. for image-forming layer of lithog. printing plates)

IT Lithographic plates

(precursors, neg.-working, photosensitive; photopolymerizable photoimaging resin compns. for image-forming layer of lithog. printing plates)

IT 849240-84-2 849240-85-3 849240-86-4 849240-87-5

849240-88-6 849240-89-7 849240-91-1

849240-92-2 849240-94-4 849240-95-5 849240-96-6

849240-97-7 849240-99-9 849241-01-6 849241-02-7 849241-03-8

849241-04-9 849241-06-1

RL: TEM (Technical or engineered material use); USES (Uses)
(resin in photopolymerizable photoimaging resin compns.)

L29 ANSWER 8 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2005:302458 HCAPLUS

DOCUMENT NUMBER: 142:382209

TITLE: Photopolymerizable photoimaging resin compositions for image-forming layer of lithographic printing plates

INVENTOR(S): Kunita, Kazuto

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 98 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005091617	A2	20050407	JP 2003-323410	20030916
PRIORITY APPLN. INFO.:			JP 2003-323410	20030916

AB The composition contains 2 kinds of alkali-solubilizable radically-crosslinkable polymers, wherein one of the polymer has styrene groups and alkali-solubilizable groups in the side chain and wherein the other polymer has (meth)acryl groups and alkali-solubilizable groups in the side chain. The composition shows high sensitivity and good storageability and provides good developing characteristics.

IT 761432-20-6 790685-30-2 849435-06-9

RL: TEM (Technical or engineered material use); USES (Uses)
 (resin in photopolymerizable photoimaging resin compns.)

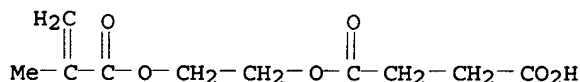
RN 761432-20-6 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 2-methyl-N-phenyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

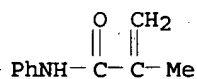
CMF C10 H14 O6



CM 2

CRN 1611-83-2

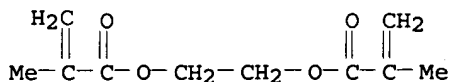
CMF C10 H11 N O



CM 3

CRN 97-90-5

CMF C10 H14 O4



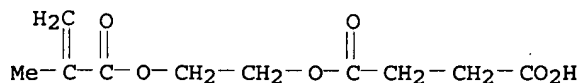
RN 790685-30-2 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-(4-hydroxyphenyl)-2-methyl-2-propenamide, methyl 2-methyl-2-propenoate and 2-[(2-methyl-1-oxo-2-propenyl)amino]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

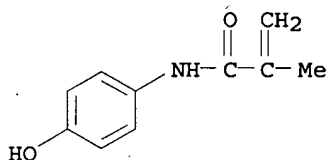
CMF C10 H14 O6



CM 2

CRN 19243-95-9

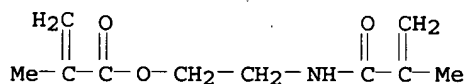
CMF C10 H11 N O2



CM 3

CRN 6206-58-2

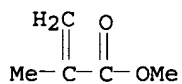
CMF C10 H15 N O3



CM 4

CRN 80-62-6

CMF C5 H8 O2



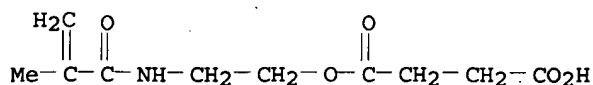
RN 849435-06-9 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)amino]ethyl] ester, polymer with 2-[(2-methyl-1-oxo-2-propenyl)amino]ethyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 86126-56-9

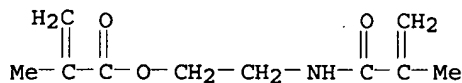
CMF C10 H15 N O5



CM 2

CRN 6206-58-2

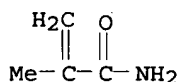
CMF C10 H15 N O3



CM 3

CRN 79-39-0

CMF C4 H7 N O



IC ICM G03F0007-038

ICS C08F0290-08; G03F0007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 37

ST photopolymerizable photoimaging compn resin lithog **printing** plate

IT Photoimaging materials
(photopolymerizable; photopolymerizable photoimaging resin compns. for image-forming layer of lithog. **printing** plates)

IT Lithographic plates
(**precursors**, neg.-working, photosensitive; photopolymerizable photoimaging resin compns. for image-forming layer of lithog. **printing** plates)

IT 50583-46-5 207730-92-5 491080-47-8 657414-44-3 657414-50-1
766349-54-5 **761432-20-6** 790685-25-5 **790685-30-2**
791124-32-8 849435-05-8 **849435-06-9** 849435-07-0
849435-09-2 849435-10-5 849435-11-6 849435-12-7 849435-52-5
849435-53-6 849435-54-7 849435-56-9 849435-59-2 849435-61-6

RL: TEM (Technical or engineered material use); USES (Uses)
(resin in photopolymerizable photoimaging resin compns.)

L29 ANSWER 9 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2005:212591 HCAPLUS

DOCUMENT NUMBER: 142:306466

TITLE: Photopolymerizable photoimaging composition and negatively-working directly-imaging lithographic **printing** plate **precursors** therefrom

INVENTOR(S): Fujimaki, Kazuhiro

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 81 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005062482	A2	20050310	JP 2003-292530	20030812
PRIORITY APPLN. INFO.:			JP 2003-292530	20030812

AB The title composition contains a radical polymerization initiator, a radical polymerization co-initiator of ≤ 1.10 V oxidation potential, an IR-absorber, and radically polymerizable compds. The composition shows high sensitivity and good storageability and provides highly durable layers.

IT 761432-20-6 847565-07-5

RL: TEM (Technical or engineered material use); USES (Uses)
(radically polymerizable compds. in composition)

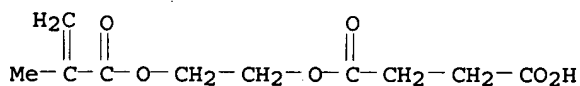
RN 761432-20-6 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 2-methyl-N-phenyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

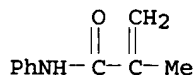
CMF C10 H14 O6



CM 2

CRN 1611-83-2

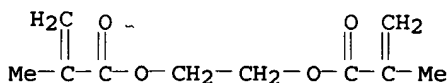
CMF C10 H11 N O



CM 3

CRN 97-90-5

CMF C10 H14 O4



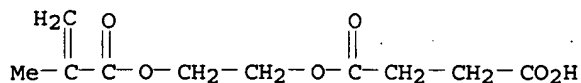
RN 847565-07-5 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 2-methyl-2-propenamide and 2-propenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

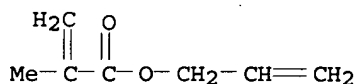
CMF C10 H14 O6



CM 2

CRN 96-05-9

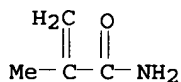
CMF C7 H10 O2



CM 3

CRN 79-39-0

CMF C4 H7 N O



IC ICM G03F0007-029

ICS C08F0002-44; C08F0002-50; G03F0007-004; G03F0007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST photopolymerizable photoimaging compn neg lithog **printing plate precursor**

IT Lithographic plates

(photopolymerizable photoimaging composition and neg.-working directly-imaging lithog. **printing plate precursors** therefrom)

IT Photoimaging materials

(photopolymerizable; photopolymerizable photoimaging composition and neg.-working directly-imaging lithog. **printing plate precursors** therefrom)IT 29570-58-9 80937-22-0 91105-84-9 **761432-20-6****847565-07-5** 847573-65-3RL: TEM (Technical or engineered material use); USES (Uses)
(radically polymerizable compds. in composition)

L29 ANSWER 10 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2005:209978 HCAPLUS

DOCUMENT NUMBER: 142:306465

TITLE: Photopolymerizable photoimaging composition and negatively-working directly-imaging lithographic **printing plate precursors** made thereof

INVENTOR(S): Fujimaki, Kazuhiro

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 81 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005062478	A2	20050310	JP 2003-292453	20030812
PRIORITY APPLN. INFO.:			JP 2003-292453	20030812

AB The title composition contains a compound with an amino groups and hydroxy groups, an IR-absorber, a radical polymerization initiator, and ethylenic unsatd. compds. The composition shows high sensitivity and good storageability and provides highly durable layers.

IT 761432-20-6 847565-07-5

RL: TEM (Technical or engineered material use); USES (Uses)
 (ethylenic unsatd. compds. in composition)

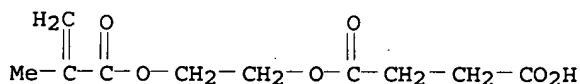
RN 761432-20-6 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 2-methyl-N-phenyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

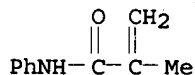
CMF C10 H14 O6



CM 2

CRN 1611-83-2

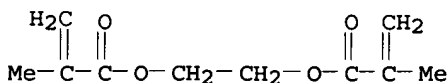
CMF C10 H11 N O



CM 3

CRN 97-90-5

CMF C10 H14 O4



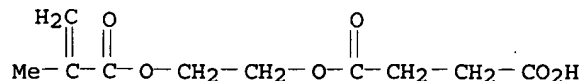
RN 847565-07-5 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 2-methyl-2-propenamide and 2-propenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

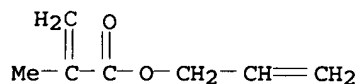
CMF C10 H14 O6



CM 2

CRN 96-05-9

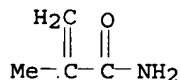
CMF C7 H10 O2



CM 3

CRN 79-39-0

CMF C4 H7 N O



IC ICM G03F0007-004

ICS C08F0002-44; G03F0007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST photopolymerizable photoimaging compn neg lithog **printing plate precursor**

IT Photolithography

(photopolymerizable photoimaging composition and neg.-working directly-imaging lithog. **printing plate precursors** therefrom)

IT Photoimaging materials

(photopolymerizable; photopolymerizable photoimaging composition and neg.-working directly-imaging lithog. **printing plate precursors** therefrom)

IT 761432-20-6 847565-07-5

RL: TEM (Technical or engineered material use); USES (Uses) (ethylenic unsatd. compds. in composition)

L29 ANSWER 11 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2005:160797 HCAPLUS

DOCUMENT NUMBER: 142:269262

TITLE: Image recording material for IR-sensitive **planographic printing plate**

INVENTOR(S): Tsuchimura, Tomotaka

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: U.S. Pat. Appl. Publ., 36 pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005043173	A1	20050224	US 2004-921860	20040820
JP 2005070269	A2	20050317	JP 2003-298432	20030822
PRIORITY APPLN. INFO.:			JP 2003-298432	A 20030822

AB The heat mode image recording material of the present invention comprises an IR absorbent (A), and a polymer (B) comprising a polyfunctional monomer component. The material can be exposed to an IR laser, whereby an image can be formed thereon. The heat mode image recording material of the invention has superior film-formability and superior film strength, and is useful for a the recording layer of a **planog. printing plate precursor** having wide development latitude and excellent scratch resistance.

IT 845831-57-4 845831-67-6

RL: NUU (Other use, unclassified); PRP (Properties); USES (Uses)
(image recording material for IR-sensitive **planog. printing plate**)

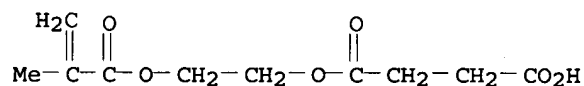
RN 845831-57-4 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with ethyl 2-methyl-2-propenoate and N,N'-methylenebis[2-propenamide] (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

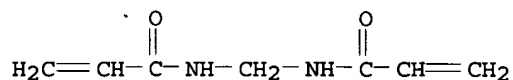
CMF C10 H14 O6



CM 2

CRN 110-26-9

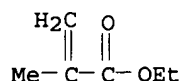
CMF C7 H10 N2 O2



CM 3

CRN 97-63-2

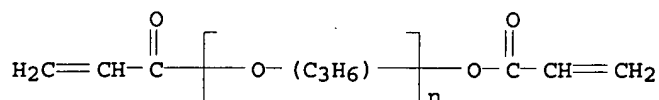
CMF C6 H10 O2



RN 845831-67-6 HCAPLUS
 CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with N-(1-methylethyl)-2-propenamide and
 α -(1-oxo-2-propenyl)- ω -[(1-oxo-2-
 propenyl)oxy]poly[oxy(methyl-1,2-ethanediyl)] (9CI) (CA INDEX NAME)

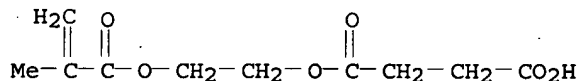
CM 1

CRN 52496-08-9
 CMF (C3 H6 O)_n C6 H6 O3
 CCI IDS, PMS



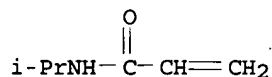
CM 2

CRN 20882-04-6
 CMF C10 H14 O6



CM 3

CRN 2210-25-5
 CMF C6 H11 N O



IC ICM B41M0005-20
 INCL 503201000
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and
 Other Reprographic Processes)
 Section cross-reference(s): 35, 38
 ST IR sensitive **planog printing** recording plate
 polymer
 IT Lithographic plates
 (computer-to-plate; Image recording material for IR-sensitive
planog. printing plate)
 IT 407089-74-1 845831-57-4 845831-58-5 845831-60-9
 845831-61-0 845831-62-1 845831-64-3 845831-65-4 845831-66-5
 845831-67-6 845831-68-7 845831-69-8 845831-70-1
 845831-71-2 845834-76-6
 RL: NUU (Other use, unclassified); PRP (Properties); USES (Uses)
 (image recording material for IR-sensitive **planog.**
printing plate)

L29 ANSWER 12 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 2005:122676 HCAPLUS
 DOCUMENT NUMBER: 142:228751
 TITLE: Radical polymerizable composition and

lithographic printing plate
precursor using the same
Kakino, Ryuki; Kunita, Kazuto
Fuji Photo Film Co., Ltd., Japan
U.S. Pat. Appl. Publ., 45 pp.
CODEN: USXXCO
Patent
English
DOCUMENT TYPE:
LANGUAGE:
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005031986	A1	20050210	US 2004-900169	20040728
JP 2005062856	A2	20050310	JP 2004-220626	20040728
PRIORITY APPLN. INFO.:			JP 2003-202332	A 20030728

AB A radical polymerizable composition comprises (A) an alkali-soluble resin containing a radical polymerizable group, (B) a radical polymerizable compound, and (C) a radical initiator, wherein reactivity of a polymerizable group of the polymerizable compound (B) to a polymerizable group of the polymerizable compound (B) is larger than reactivity of a polymerizable group of the polymerizable compound (B) to a radical polymerizable group of the alkali-soluble resin (A), and a reactivity of a radical polymerizable group of the alkali-soluble resin (A) to a polymerizable group of the polymerizable compound (B) is larger than reactivity of a radical polymerizable group of the alkali-soluble resin (A) to a radical polymerizable group of the alkali-soluble resin (A).

IT 840488-55-3P

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(radical polymerizable composition for lithog. printing plate precursor containing)

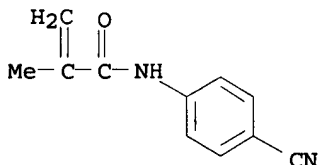
RN 840488-55-3 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-(4-cyanophenyl)-2-methyl-2-propenamide and 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 2-butenate (9CI) (CA INDEX NAME)

CM 1

CRN 90617-02-0

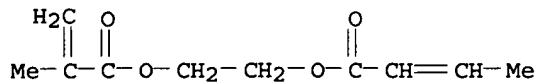
CMF C11 H10 N2 O



CM 2

CRN 72300-16-4

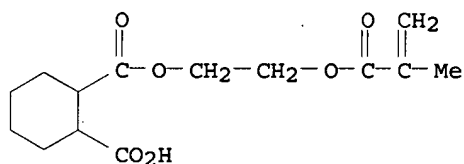
CMF C10 H14 O4



CM 3

CRN 51252-88-1

CMF C14 H20 O6



IC ICM G03C0001-76

INCL 430270100

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 35, 38

ST radical polymerizable compn lithog printing plate precursor

IT Lithographic plates

(radical polymerizable composition and lithog. printing plate precursor using same)

IT 840488-52-0P 840488-53-1P 840488-54-2P 840488-55-3P
840488-56-4P 840488-57-5P 840488-58-6P 840488-60-0P
840488-61-1PRL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(radical polymerizable composition for lithog. printing plate precursor containing)

IT 1985-51-9 3290-92-4 29570-58-9 79559-96-9 158464-09-6

RL: TEM (Technical or engineered material use); USES (Uses)
(radical polymerizable composition for lithog. printing plate precursor containing)

L29 ANSWER 13 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2004:904401 HCAPLUS

DOCUMENT NUMBER: 141:386417

TITLE: Photopolymerizable resin composition for negative-working lithographic printing plate precursors

INVENTOR(S): Kakino, Ryuki; Kunita, Kazuto
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 90 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent
LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004302184	A2	20041028	JP 2003-95552	20030331

Ross Shipe EIC 1700 Remsen 4B31 571/272-6018

PRIORITY APPLN. INFO.:

JP 2003-95552

200303

31

AB The title composition contains an alkali-solubilizable block copolymer, polymerizable compds., and a polymerization initiator, wherein the resin has at least one repeating unit having an alkali-solubilizable group. The title composition provides printing plate precursor of good development characteristics and printing plate of high printing durability.

IT 657414-36-3P 658050-90-9P 782483-51-6P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(block copolymer resin in photopolymerizable resin composition)

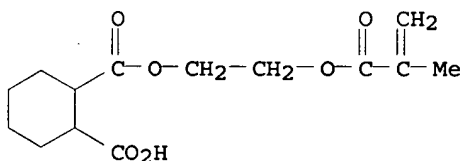
RN 657414-36-3 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 51252-88-1

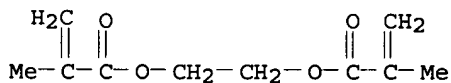
CMF C14 H20 O6



CM 2

CRN 97-90-5

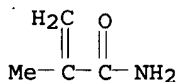
CMF C10 H14 O4



CM 3

CRN 79-39-0

CMF C4 H7 N O

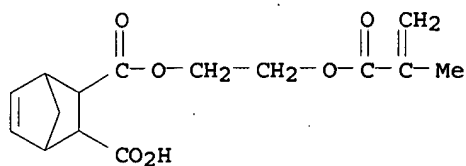


RN 658050-90-9 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2,3-dicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

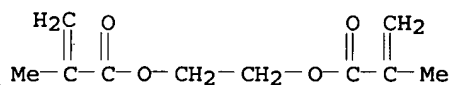
CM 1

CRN 64680-73-5
CMF C15 H18 O6



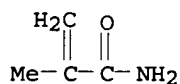
CM 2

CRN 97-90-5
CMF C10 H14 O4



CM 3

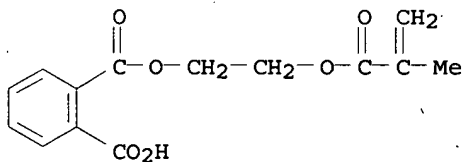
CRN 79-39-0
CMF C4 H7 N O



RN 782483-51-6 HCAPLUS
CN 1,2-Benzenedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxyl]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

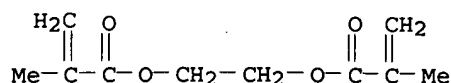
CM 1

CRN 27697-00-3
CMF C14 H14 O6



CM 2

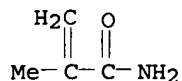
CRN 97-90-5
CMF C10 H14 O4



CM 3

CRN 79-39-0

CMF C4 H7 N O



IC ICM G03F0007-038
ICS C08F0290-12; G03F0007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 37
ST photopolymerizable resin compn neg lithog **printing plate precursor**
IT Lithographic plates
(photopolymerizable resin composition for neg.-working lithog. **printing plate precursors**)
IT Photoimaging materials
(photopolymerizable; photopolymerizable resin composition for neg.-working lithog. **printing plate precursors**)
IT 49736-69-8DP, dehydrobrominated 49736-69-8P 50583-46-5DP, dehydrobrominated 50583-46-5P **657414-36-3P**
657414-37-4P 657414-50-1P **658050-90-9P** 658705-94-3P
681127-05-9P **782483-51-6P** 782483-54-9P 782483-55-0P
782496-94-0P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(block copolymer resin in photopolymerizable resin composition)

L29 ANSWER 14 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2004:904378 HCAPLUS

DOCUMENT NUMBER: 141:386414

TITLE: Photopolymerizable resin composition for negative-working lithographic **printing plate precursors**INVENTOR(S): Kakino, Ryuki; Kunita, Kazuto
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 89 pp.
CODEN: JKXXAFDOCUMENT TYPE: Patent
LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004302077	A2	20041028	JP 2003-94320	20030331
PRIORITY APPLN. INFO.:			JP 2003-94320	20030331

AB The title composition contains a alkali-solubilizable polymer, polymerizable compds., and a polymerization initiator, wherein the polymer is a graft polymer. The composition is suitable for exposed with a laser beam.

IT 657414-36-3P 658050-90-9P 782483-51-6P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(photopolymerizable resin composition for lithog. printing plate precursors)

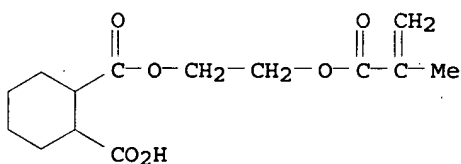
RN 657414-36-3 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 51252-88-1

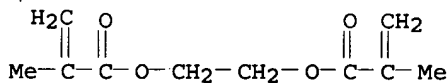
CMF C14 H20 O6



CM 2

CRN 97-90-5

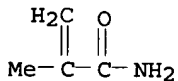
CMF C10 H14 O4



CM 3

CRN 79-39-0

CMF C4 H7 N O



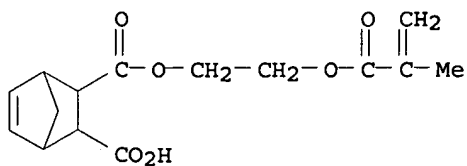
RN 658050-90-9 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2,3-dicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 64680-73-5

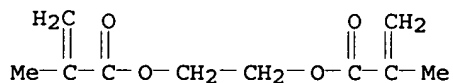
CMF C15 H18 O6



CM 2

CRN 97-90-5

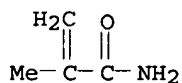
CMF C10 H14 O4



CM 3

CRN 79-39-0

CMF C4 H7 N O



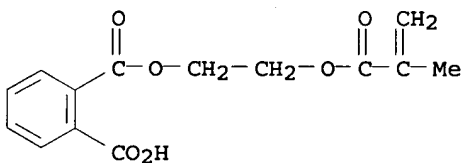
RN 782483-51-6 HCAPLUS

CN 1,2-Benzenedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 27697-00-3

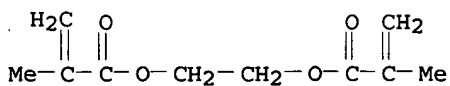
CMF C14 H14 O6



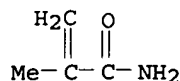
CM 2

CRN 97-90-5

CMF C10 H14 O4



CM 3

CRN 79-39-0
CMF C4 H7 N O

IC ICM G03F0007-038
ICS C08F0290-12; G03F0007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 37
ST photopolymerizable resin compn neg lithog printing plate precursor
IT Lithographic plates
(neg.-working precursors; photopolymerizable resin composition for lithog. printing plate precursors)
IT 106-91-2DP, Glycidyl methacrylate, reaction product with 3-mercaptopropionic acid modified acrylic polymer 107-96-ODP, 3-Mercaptopropionic acid, reaction product with acrylic polymer 657414-39-6DP, dehydrobrominated, reaction product with 3-mercaptopropionic acid and glycidyl methacrylate
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(photopolymerizable resin composition for lithog. printing plate precursors)
IT 49736-69-8P 657414-36-3P 657414-37-4P 657414-39-6P 657414-44-3P 657414-50-1P 658050-90-9P 658705-81-8P 658705-94-3P 681127-05-9P 782483-51-6P 782483-54-9P 782483-55-0P 782483-56-1P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(photopolymerizable resin composition for lithog. printing plate precursors)

L29 ANSWER 15 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2004:779269 HCAPLUS
DOCUMENT NUMBER: 141:285849
TITLE: IR-sensitive direct-imaging lithographic printing plate precursors
INVENTOR(S): Nagashima, Akira
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 29 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004264747	A2	20040924	JP 2003-57123	20030304
CN 1527137	A	20040908	CN 2003-10114267	20031112
PRIORITY APPLN. INFO.:			JP 2003-57123	A 20030304

AB The title printing plate precursor has an olefinic resin, a novolak resin, and a light-to-heat converting compound on a hydrophilized support, wherein the olefinic resin is a copolymer of $\text{H}_2\text{C}=\text{C}(-\text{R}_1)(-\text{X}-\text{COOH})$ ($\text{R}_1 = \text{H}$, alkyl; $\text{X} = \text{arylene}$, $-\text{CO}-\text{Y}-$, $-\text{OCO}-\text{Y}-$, $-\text{Ar}-\text{Y}-$; $\text{Y} = 2$ -valent connecting group; $\text{Ar} = \text{arylene}$) and (meth)acrylate, a (meth)acrylamide derivative, or a styrene derivative and wherein the surface of the support is electrochem. roughened in acidic solution mainly containing hydrogen chloride. The printing plate precursor shows wide development latitude and provides printing plate of high printing durability.

IT 604813-56-1 604813-62-9

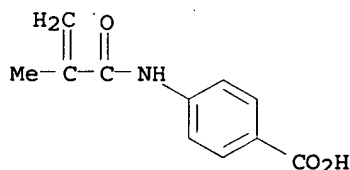
RL: TEM (Technical or engineered material use); USES (Uses)
(IR-sensitive direct-imaging lithog. printing plate precursors)

RN 604813-56-1 HCAPLUS

CN Benzoic acid, 4-[(2-methyl-1-oxo-2-propenyl)amino]-, polymer with N-[3-(dimethylamino)propyl]-2-propenamide (9CI) (CA INDEX NAME)

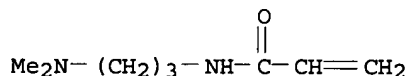
CM 1

CRN 15286-99-4
CMF C11 H11 N O3



CM 2

CRN 3845-76-9
CMF C8 H16 N2 O

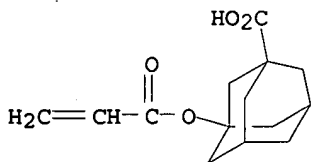


RN 604813-62-9 HCAPLUS

CN Tricyclo[3.3.1.1^{3,7}]decane-1-carboxylic acid, 3-[(1-oxo-2-propenyl)oxy]-, polymer with 1-chloro-4-(1-methylethenyl)benzene, N,N-dimethyl-2-propenamide and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

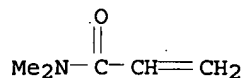
CRN 124889-09-4
CMF C14 H18 O4



CM 2

CRN 2680-03-7

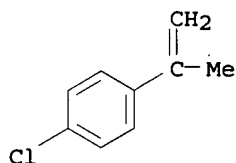
CMF C5 H9 N O



CM 3

CRN 1712-70-5

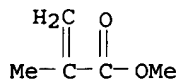
CMF C9 H9 Cl



CM 4

CRN 80-62-6

CMF C5 H8 O2



IC ICM G03F0007-033

ICS B41N0001-08; B41N0003-03; G03F0007-004; G03F0007-09

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 35

ST IR lithog **printing** plate **precursor** support resin

IT Lithographic plates

(IR-sensitive direct-imaging lithog. **printing** plate **precursors**)

IT Phenolic resins, uses

RL: TEM (Technical or engineered material use); USES (Uses)

(novolak; IR-sensitive direct-imaging lithog. **printing** plate **precursors**)

IT 7647-01-0, Hydrogen chloride, processes 27029-76-1

RL: CPS (Chemical process); PEP (Physical, engineering or chemical process); PROC (Process)

(IR-sensitive direct-imaging lithog. **printing** plate **precursors**)IT 604813-23-2 **604813-56-1** 604813-57-2 **604813-62-9**

604813-64-1 604813-65-2 604813-66-3 760965-90-0

RL: TEM (Technical or engineered material use); USES (Uses)

(IR-sensitive direct-imaging lithog. **printing** plate **precursors**)

IT 1344-09-8, Sodium silicate

RL: CPS (Chemical process); PEP (Physical, engineering or chemical process); PROC (Process)

(hydrophilizing agent; IR-sensitive direct-imaging lithog.

printing plate precursors)
 IT 37321-70-3, JIS A1050
 RL: DEV (Device component use); USES (Uses)
 (support; IR-sensitive direct-imaging lithog. printing
 plate precursors)

L29 ANSWER 16 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 2004:612321 HCAPLUS
 DOCUMENT NUMBER: 141:148156
 TITLE: Method for making lithographic printing
 plates by direct IR-imaging process
 INVENTOR(S): Kawauchi, Ikuo; Nagase, Hiroyuki
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 37 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004212649	A2	2004/07/29	JP 2002-382229	2002/12/27
PRIORITY APPLN. INFO.:			JP 2002-382229	2002/12/27

AB The title method includes the steps of: imagewise exposing a
 printing plate precursor having an image-forming
 layer on a support; and developing the image with an alkali
 developer, wherein the image-forming layer contains a copolymer of
 $\text{CH}_2=\text{C}(\text{R})(-\text{X}-\text{COOH})$ ($\text{R} = \text{H}$, alkyl; $\text{X} = \text{arylene}$) and wherein the
 developer contains an anionic surfactant having sulfonium groups.
 The method uses decreased exposure energy and generates little
 residue film in the development.

IT 604813-42-5P 604813-43-6P 604813-44-7P
 604813-45-8P 604813-46-9P 604813-47-0P
 604813-48-1P 604813-55-0P 604813-56-1P
 604813-59-4P 604813-60-7P 604813-61-8P
 604813-62-9P 722484-52-8P 722494-08-8P
 722494-09-9P

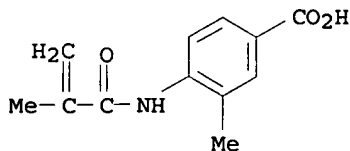
RL: SPN (Synthetic preparation); TEM (Technical or engineered
 material use); PREP (Preparation); USES (Uses)
 (copolymer; light-sensitive layer of lithog. printing
 plate precursors)

RN 604813-42-5 HCAPLUS

CN Benzoic acid, 3-methyl-4-[(2-methyl-1-oxo-2-propenyl)amino]-,
 polymer with N,N,2-trimethyl-2-propenamide (9CI) (CA INDEX NAME)

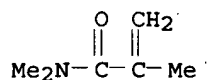
CM 1

CRN 604813-37-8
 CMF C12 H13 N O3



CM 2

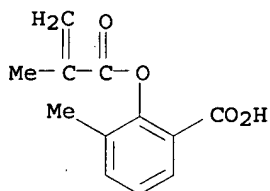
CRN 6976-91-6
CMF C6 H11 N O



RN 604813-43-6 HCAPLUS
CN Benzoic acid, 3-methyl-2-[(2-methyl-1-oxo-2-propenyl)oxy]-, polymer
with 2-methyl-N-phenyl-2-propenamide (9CI) (CA INDEX NAME)

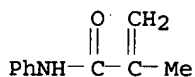
CM 1

CRN 604813-39-0
CMF C12 H12 O4



CM 2

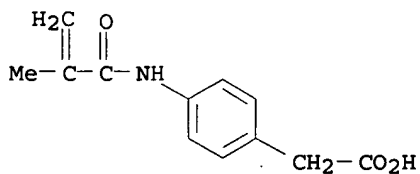
CRN 1611-83-2
CMF C10 H11 N O



RN 604813-44-7 HCAPLUS
CN Benzeneacetic acid, 4-[(2-methyl-1-oxo-2-propenyl)amino]-, polymer
with N-[3-(dimethylamino)propyl]-2-propenamide (9CI) (CA INDEX
NAME)

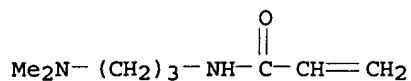
CM 1

CRN 54290-27-6
CMF C12 H13 N O3



CM 2

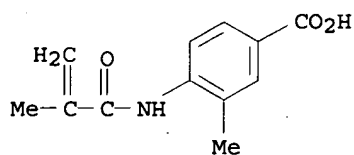
CRN 3845-76-9
CMF C8 H16 N2 O



RN 604813-45-8 HCAPLUS
CN Benzoic acid, 3-methyl-4-[(2-methyl-1-oxo-2-propenyl)amino]-, polymer with N-(1,1-dimethylethyl)-2-propenamide and 1-ethenyl-2-fluorobenzene (9CI) (CA INDEX NAME)

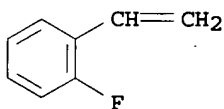
CM 1

CRN 604813-37-8
CMF C12 H13 N O3



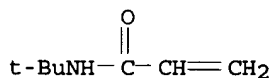
CM 2

CRN 394-46-7
CMF C8 H7 F



CM 3

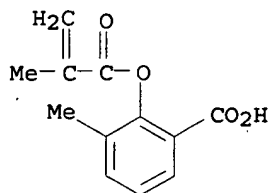
CRN 107-58-4
CMF C7 H13 N O



RN 604813-46-9 HCAPLUS
CN Benzoic acid, 3-methyl-2-[(2-methyl-1-oxo-2-propenyl)oxy]-, polymer with N-(butoxymethyl)-2-propenamide and 1-ethenyl-2-fluorobenzene (9CI) (CA INDEX NAME)

CM 1

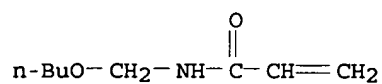
CRN 604813-39-0
CMF C12 H12 O4



CM 2

CRN 1852-16-0

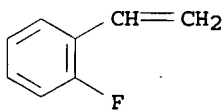
CMF C8 H15 N O2



CM 3

CRN 394-46-7

CMF C8 H7 F



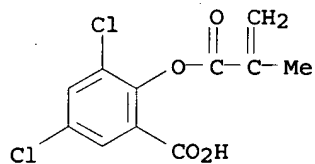
RN 604813-47-0 HCAPLUS

CN Benzoic acid, 3,5-dichloro-2-[(2-methyl-1-oxo-2-propenyl)oxy]-,
polymer with N-(butoxymethyl)-2-propenamide, 1-chloro-3-
ethenylbenzene and methyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 165323-50-2

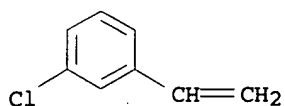
CMF C11 H8 Cl2 O4



CM 2

CRN 2039-85-2

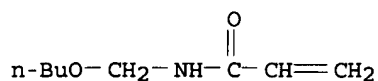
CMF C8 H7 Cl



CM 3

CRN 1852-16-0

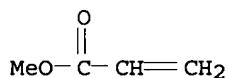
CMF C8 H15 N O2



CM 4

CRN 96-33-3

CMF C4 H6 O2



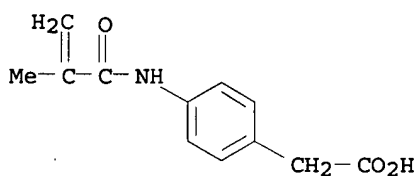
RN 604813-48-1 HCAPLUS

CN Benzeneacetic acid, 4-[(2-methyl-1-oxo-2-propenyl)amino]-, polymer with N-(butoxymethyl)-2-propenamide, 1-chloro-4-ethenylbenzene and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 54290-27-6

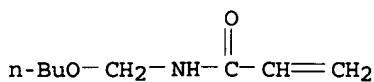
CMF C12 H13 N O3



CM 2

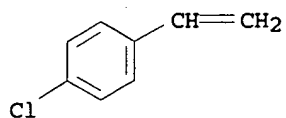
CRN 1852-16-0

CMF C8 H15 N O2



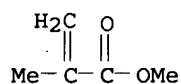
CM 3

CRN 1073-67-2
CMF C8 H7 Cl



CM 4

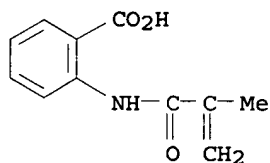
CRN 80-62-6
CMF C5 H8 O2



RN 604813-55-0 HCAPLUS
CN Benzoic acid, 2-[(2-methyl-1-oxo-2-propenyl)amino]-, polymer with
N-(1,1-dimethylethyl)-2-methyl-2-propenamide (9CI) (CA INDEX NAME)

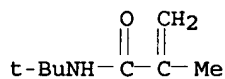
CM 1

CRN 7600-39-7
CMF C11 H11 N O3



CM 2

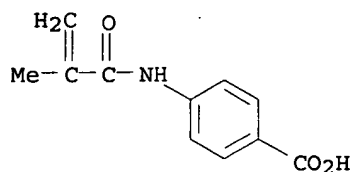
CRN 6554-73-0
CMF C8 H15 N O



RN 604813-56-1 HCAPLUS
CN Benzoic acid, 4-[(2-methyl-1-oxo-2-propenyl)amino]-, polymer with
N-[3-(dimethylamino)propyl]-2-propenamide (9CI) (CA INDEX NAME)

CM 1

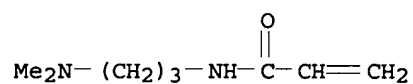
CRN 15286-99-4
CMF C11 H11 N O3



CM 2

CRN 3845-76-9

CMF C8 H16 N2 O



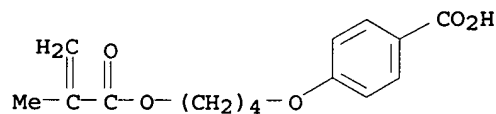
RN 604813-59-4 HCAPLUS

CN Benzoic acid, 4-[4-[(2-methyl-1-oxo-2-propenyl)oxy]butoxy]-, polymer with 1-chloro-4-(1-methylethenyl)benzene and N,N-dimethyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 92174-21-5

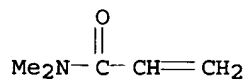
CMF C15 H18 O5



CM 2

CRN 2680-03-7

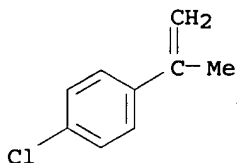
CMF C5 H9 N O



CM 3

CRN 1712-70-5

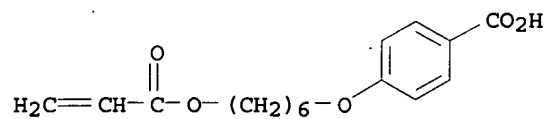
CMF C9 H9 Cl



RN 604813-60-7 HCAPLUS
 CN Benzoic acid, 4-[[6-[(1-oxo-2-propenyl)oxy]hexyl]oxy]-, polymer with
 1-chloro-4-(1-methylethenyl)benzene and N-[3-(dimethylamino)propyl]-
 2-propenamide (9CI) (CA INDEX NAME)

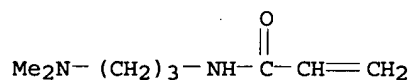
CM 1

CRN 83883-26-5
 CMF C16 H20 O5



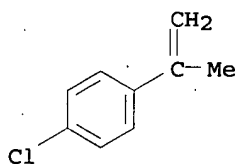
CM 2

CRN 3845-76-9
 CMF C8 H16 N2 O



CM 3

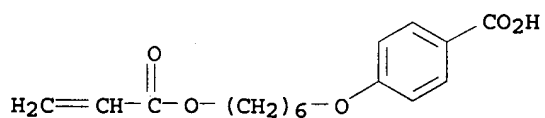
CRN 1712-70-5
 CMF C9 H9 Cl



RN 604813-61-8 HCAPLUS
 CN Benzoic acid, 4-[[6-[(1-oxo-2-propenyl)oxy]hexyl]oxy]-, polymer with
 1-chloro-4-(1-methylethenyl)benzene, N-[3-(dimethylamino)propyl]-2-
 propenamide and methyl 2-propenoate (9CI) (CA INDEX NAME)

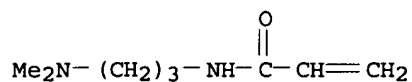
CM 1

CRN 83883-26-5
 CMF C16 H20 O5



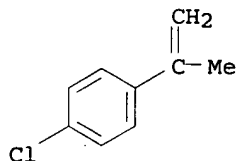
CM 2

CRN 3845-76-9
CMF C8 H16 N2 O



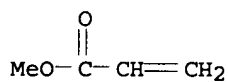
CM 3

CRN 1712-70-5
CMF C9 H9 Cl



CM 4

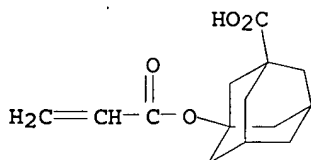
CRN 96-33-3
CMF C4 H6 O2



RN 604813-62-9 HCAPLUS
CN Tricyclo[3.3.1.1^{3,7}]decane-1-carboxylic acid, 3-[(1-oxo-2-propenyl)oxy]-, polymer with 1-chloro-4-(1-methylethenyl)benzene, N,N-dimethyl-2-propenamide and methyl 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

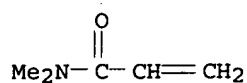
CM 1

CRN 124889-09-4
CMF C14 H18 O4



CM 2

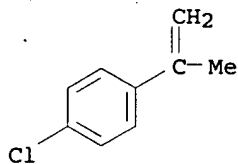
CRN 2680-03-7
CMF C5 H9 N O



CM 3

CRN 1712-70-5

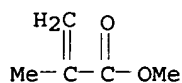
CMF C9 H9 Cl



CM 4

CRN 80-62-6

CMF C5 H8 O2



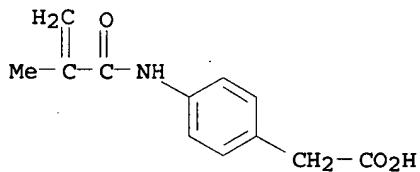
RN 722484-52-8 HCAPLUS

CN Benzeneacetic acid, 4-[(2-methyl-1-oxo-2-propenyl)aminol]-, polymer with N-(butoxymethyl)-2-propenamide, 1-ethenyl-4-fluorobenzene and ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 54290-27-6

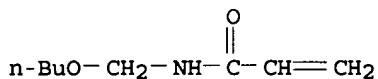
CMF C12 H13 N O3



CM 2

CRN 1852-16-0

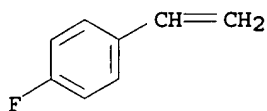
CMF C8 H15 N O2



CM 3

CRN 405-99-2

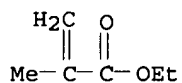
CMF C8 H7 F



CM 4

CRN 97-63-2

CMF C6 H10 O2



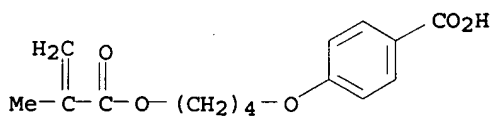
RN 722494-08-8 HCAPLUS

CN Benzoic acid, 4-[4-[(2-methyl-1-oxo-2-propenyl)oxy]butoxy]-, polymer with (chloromethyl)ethenylbenzene and N-(1,1-dimethylethyl)-2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 92174-21-5

CMF C15 H18 O5



CM 2

CRN 30030-25-2

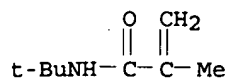
CMF C9 H9 Cl

CCI IDS

D1-CH₂-ClD1-CH=CH₂

CM 3

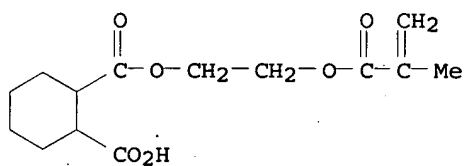
CRN 6554-73-0
CMF C8 H15 N O



RN 722494-09-9 HCAPLUS
CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with
(chloromethyl)ethenylbenzene, N,N-dimethyl-2-propenamide and ethyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 51252-88-1
CMF C14 H20 O6



CM 2

CRN 30030-25-2
CMF C9 H9 Cl
CCI IDS

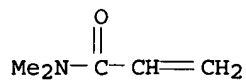


D1-CH₂-Cl

D1-CH=CH₂

CM 3

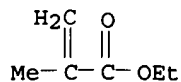
CRN 2680-03-7
CMF C5 H9 N O



CM 4

CRN 97-63-2

CMF C6 H10 O2



IC ICM G03F0007-00
ICS G03F0007-033; G03F0007-32
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 46
ST lithog **printing** plate surfactant copolymer
IT Surfactants
(anionic; developer for lithog. **printing** plate)
IT Lithographic plates
(method making lithog. **printing** plates)
IT 146115-88-0P 188601-29-8P 604813-16-3P 604813-18-5P
604813-19-6P 604813-23-2P 604813-38-9P 604813-40-3P
604813-41-4P 604813-42-5P 604813-43-6P
604813-44-7P 604813-45-8P 604813-46-9P
604813-47-0P 604813-48-1P 604813-50-5P
604813-52-7P 604813-54-9P 604813-55-0P
604813-56-1P 604813-57-2P 604813-59-4P
604813-60-7P 604813-61-8P 604813-62-9P
604813-64-1P 604813-65-2P 604813-66-3P 604813-67-4P
722484-52-8P 722494-08-8P 722494-09-9P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(copolymer; light-sensitive layer of lithog. **printing** plate **precursors**)
IT 2386-53-0, Sodium dodecylsulfonate 25638-17-9 27936-45-4
28519-02-0 51506-28-6 74523-85-6 89788-04-5
RL: CPS (Chemical process); PEP (Physical, engineering or chemical process); PROC (Process)
(developer for lithog. **printing** plate)

L29 ANSWER 17 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2004:510155 HCAPLUS
DOCUMENT NUMBER: 141:62133
TITLE: Polymerizable composition and lithographic **printing** plate **precursor**
INVENTOR(S): Shimada, Kazuto
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 73 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1431032	A1	20040623	EP 2003-29206	20031218
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
CN 1508624	A	20040630	CN 2003-10123242	20031218
US 2004137369	A1	20040715	US 2003-738305	20031218

JP 2005062800 A2 20050310 JP 2003-420733 18
 200312
 18
 PRIORITY APPLN. INFO.: JP 2002-366539 A 200212
 18
 JP 2003-202951 A 200307
 29

OTHER SOURCE(S): MARPAT 141:62133

AB The present invention relates to polymerizable composition for lithog. printing plate precursor containing: (A) a binder polymer; (B) a compound having a polymerizable unsatd. group; and (C) a compound which has a triarylsulfonium salt structure and in which a sum of Hammett's consts. of all substituents bonded to the aryl skeleton is larger than 0.46.

IT 709037-25-2

RL: PRP (Properties); TEM (Technical or engineered material use);

USES (Uses)

(binder; polymerizable composition for lithog. printing plate precursor containing)

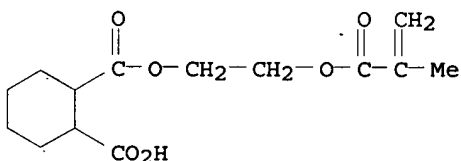
RN 709037-25-2 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-(1-methylethyl)-2-propenamide and 2-propenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 51252-88-1

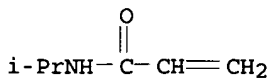
CMF C14 H20 O6



CM 2

CRN 2210-25-5

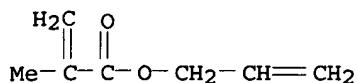
CMF C6 H11 N O



CM 3

CRN 96-05-9

CMF C7 H10 O2



IC ICM B41C0001-10
ICS B41M0005-40; G03F0007-004

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38

ST polymerizable compn lithog **printing plate precursor**

IT Lithographic plates
UV stabilizers
(polymerizable composition for lithog. **printing plate precursor**)

IT 183745-11-1 244606-76-6 709037-28-5
RL: TEM (Technical or engineered material use); USES (Uses)
(UV absorber; polymerizable composition for lithog. **printing plate precursor** containing)

IT 134490-11-2 658705-94-3 **709037-25-2** 709037-26-3
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(binder; polymerizable composition for lithog. **printing plate precursor** containing)

IT 29570-58-9, Dipentaerythritol hexaacrylate 40220-08-4, Aronix M315
RL: TEM (Technical or engineered material use); USES (Uses)
(polymerizable composition for lithog. **printing plate precursor** containing)

IT 127820-39-7 676349-80-7 709037-30-9 709037-31-0 709037-32-1
709037-34-3 709037-35-4 709037-37-6 709037-39-8 709037-41-2
709037-43-4 709037-44-5 709037-45-6 709037-46-7
RL: CAT (Catalyst use); USES (Uses)
(polymerization initiator; polymerizable composition for lithog. **printing plate precursor** containing)

L29 ANSWER 18 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2004:474736 HCAPLUS
DOCUMENT NUMBER: 141:44887
TITLE: Lithographic **printing plate precursors**
INVENTOR(S): Kunita, Kazuto
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 97 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004163853	A2	20040610	JP 2003-56970	20030304
PRIORITY APPLN. INFO.:			JP 2002-278890	A 20020925

AB The title **printing plate precursor** contains an alkali-solubilizable resin in a light- or heat-sensitive recording layer on a support, wherein the resin has a general structure:
-X-Ar-Y- (X = electron donating group; Y = electron-withdrawing group; Ar = aromatic ring). The **printing plate**

precursor shows high sensitivity, high printing durability, and good storageability.

IT 701960-50-1P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(lithog. printing plate precursors)

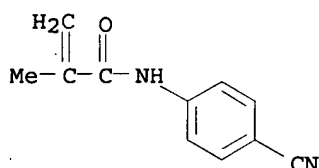
RN 701960-50-1 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-(4-cyanophenyl)-2-methyl-2-propenamide and 1,2-ethanediyl bis(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)

CM 1

CRN 90617-02-0

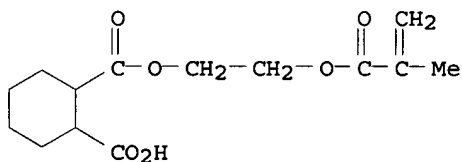
CMF C11 H10 N2 O



CM 2

CRN 51252-88-1

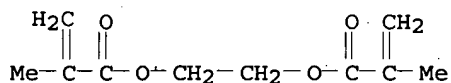
CMF C14 H20 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



IC ICM G03F0007-038

ICS G03F0007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35

ST lithog printing plate precursor

IT Lithographic plates

(lithog. printing plate precursors)

IT 657414-47-6P 701960-42-1P 701960-45-4P 701960-47-6P

701960-50-1P 701960-53-4P 701960-56-7P 701960-59-0P

701960-61-4P 701960-64-7P 701960-66-9P 701960-68-1P

701960-71-6P 701960-74-9P 701960-77-2P 701960-80-7P

701960-82-9P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(lithog. printing plate precursors)

L29 ANSWER 19 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2004:260988 HCAPLUS

DOCUMENT NUMBER: 140:312029

TITLE: Polymerizable composition and
planographic printing plate precursor

INVENTOR(S): Sugasaki, Atsushi; Kunita, Kazuto; Fujimaki, Kazuhiro

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Eur. Pat. Appl., 113 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

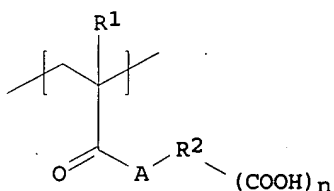
LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1403043	A2	20040331	EP 2003-22142	20030930
EP 1403043	A3	20040421		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
US 2004072101	A1	20040415	US 2003-673332	20030930
JP 2004318053	A2	20041111	JP 2003-339817	20030930
PRIORITY APPLN. INFO.:				
			JP 2002-287920	A 20020930
			JP 2003-38288	A 20030217
			JP 2003-100575	A 20030403

GI



I

AB The present invention provides a **planog. printing plate precursor** including on a support a photosensitive layer that contains a polymerizable composition containing a specific binder polymer having a repeating unit of formula I ($R_1 = H, Me$; $R_2 =$ linking group which includes two or more atoms selected from carbon atom, hydrogen, oxygen, nitrogen, sulfur and has a number of atoms of 2-82; $A = O, -NR_3-$, $R_3 = H$, monovalent C1-10-hydrocarbon; $n = 1-5$), an IR absorbent, a polymerization initiator and a polymerizable compound. The invention also provides a **planog. printing plate precursor** provided with a specific photosensitive layer with respect to an alkaline developer. The object of the present invention is to provide a **planog. printing plate precursor** that is excellent in printing durability and image formation, as well as to provide a polymerizable composition that is suitably used for a photosensitive layer of the **planog. printing plate precursor**.

IT 676349-35-2 676349-36-3 676349-37-4
676349-39-6 676349-41-0 676349-42-1
676349-56-7 676349-57-8 676349-58-9
676349-59-0 676349-60-3 676349-61-4
676349-62-5 676349-63-6 676349-64-7
676349-65-8 676349-66-9 676349-67-0
676349-69-2 676349-70-5 676349-72-7

RL: PRP (Properties); TEM (Technical or engineered material use);
USES (Uses)

(polymerizable composition and **planog. printing plate precursor**)

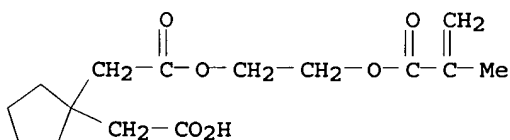
RN 676349-35-2 HCAPLUS

CN 1,1-Cyclopentanediadicetic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 393546-18-4

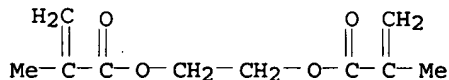
CMF C15 H22 O6



CM 2

CRN 97-90-5

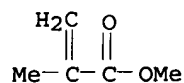
CMF C10 H14 O4



CM 3

CRN 80-62-6

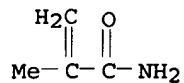
CMF C5 H8 O2



CM 4

CRN 79-39-0

CMF C4 H7 N O



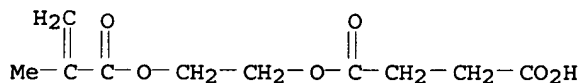
RN 676349-36-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

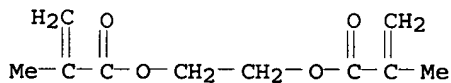
CMF C10 H14 O6



CM 2

CRN 97-90-5

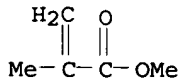
CMF C10 H14 O4



CM 3

CRN 80-62-6

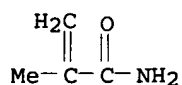
CMF C5 H8 O2



CM 4

CRN 79-39-0

CMF C4 H7 N O



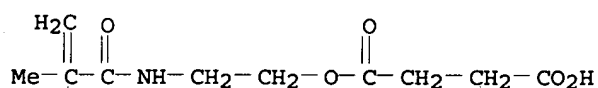
RN 676349-37-4 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)amino]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 86126-56-9

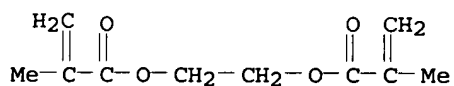
CMF C10 H15 N O5



CM 2

CRN 97-90-5

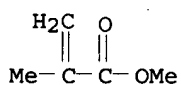
CMF C10 H14 O4



CM 3

CRN 80-62-6

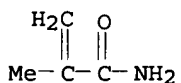
CMF C5 H8 O2



CM 4

CRN 79-39-0

CMF C4 H7 N O



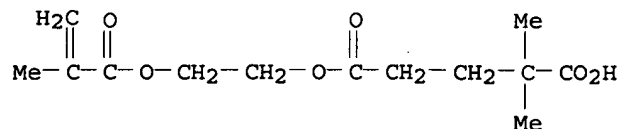
RN 676349-39-6 HCAPLUS

CN Pentanedioic acid, 2,2-dimethyl-, 5-[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 676349-38-5

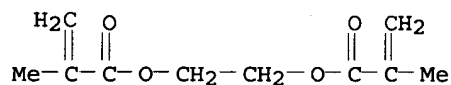
CMF C13 H20 O6



CM 2

CRN 97-90-5

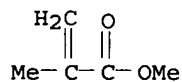
CMF C10 H14 O4



CM 3

CRN 80-62-6

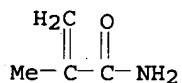
CMF C5 H8 O2



CM 4

CRN 79-39-0

CMF C4 H7 N O



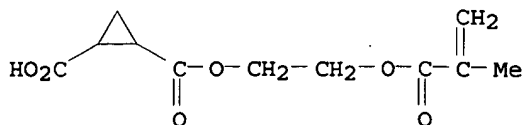
RN 676349-41-0 HCAPLUS

CN 1,2-Cyclopropanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), methyl 2-methyl-2-propenoate and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 676349-40-9

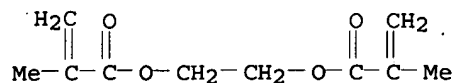
CMF C11 H14 O6



CM 2

CRN 97-90-5

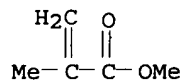
CMF C10 H14 O4



CM 3

CRN 80-62-6

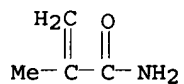
CMF C5 H8 O2



CM 4

CRN 79-39-0

CMF C4 H7 N O



RN 676349-42-1 HCAPLUS

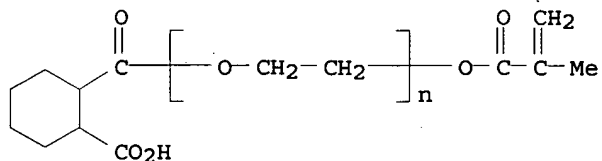
CN 2-Propenoic acid, 2-methyl-, 1,2-ethanediyl ester, polymer with
 α -[(2-carboxycyclohexyl)carbonyl]- ω -[(2-methyl-1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl), methyl 2-methyl-2-propenoate
 and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 237073-56-2

CMF (C2 H4 O)_n C12 H16 O5

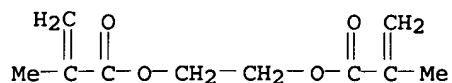
CCI PMS



CM 2

CRN 97-90-5

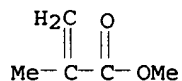
CMF C10 H14 O4



CM 3

CRN 80-62-6

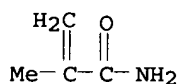
CMF C5 H8 O2



CM 4

CRN 79-39-0

CMF C4 H7 N O



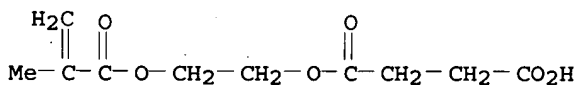
RN 676349-56-7 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]
 ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and
 N-(4-methoxyphenyl)-2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

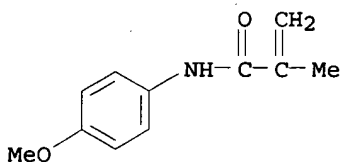
CMF C10 H14 O6



CM 2

CRN 7274-71-7

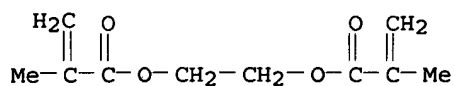
CMF C11 H13 N O2



CM 3

CRN 97-90-5

CMF C10 H14 O4



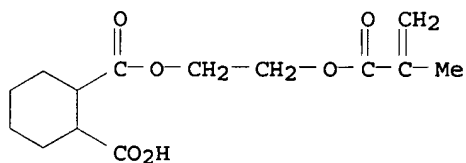
RN 676349-57-8 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and N-(4-methoxyphenyl)-2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 51252-88-1

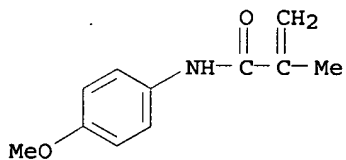
CMF C14 H20 O6



CM 2

CRN 7274-71-7

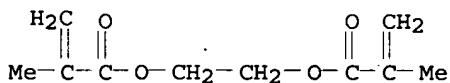
CMF C11 H13 N O2



CM 3

CRN 97-90-5

CMF C10 H14 O4



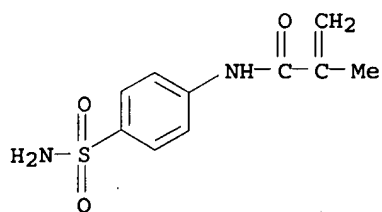
RN 676349-58-9 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-[4-(aminosulfonyl)phenyl]-2-methyl-2-propenamide and 1,2-ethanediyl bis(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)

CM 1

CRN 56992-87-1

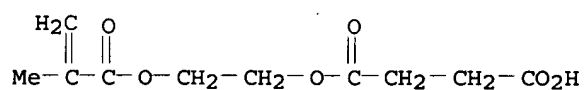
CMF C10 H12 N2 O3 S



CM 2

CRN 20882-04-6

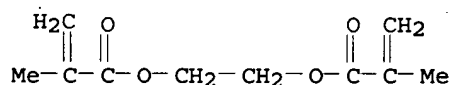
CMF C10 H14 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



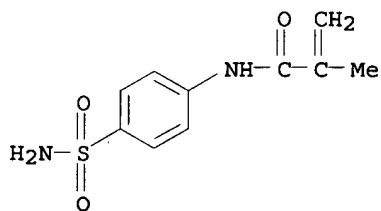
RN 676349-59-0 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-[4-(aminosulfonyl)phenyl]-2-methyl-2-propenamide and 1,2-ethanediyl bis(2-methyl-2-propenoate) (9CI) (CA INDEX NAME)

CM 1

CRN 56992-87-1

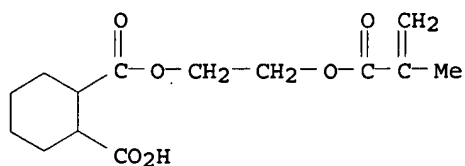
CMF C10 H12 N2 O3 S



CM 2

CRN 51252-88-1

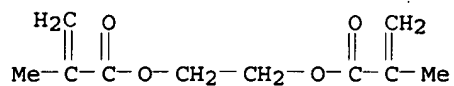
CMF C14 H20 O6



CM 3

CRN 97-90-5

CMF C10 H14 O4



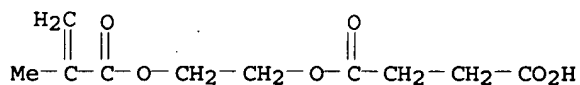
RN 676349-60-3 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate), N-(4-methoxyphenyl)-2-methyl-2-propenamide and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

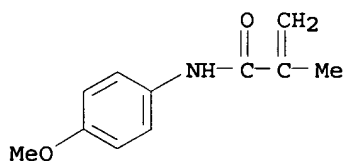
CMF C10 H14 O6



CM 2

CRN 7274-71-7

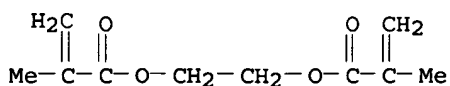
CMF C11 H13 N O2



CM 3

CRN 97-90-5

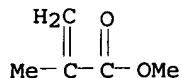
CMF C10 H14 O4



CM 4

CRN 80-62-6

CMF C5 H8 O2



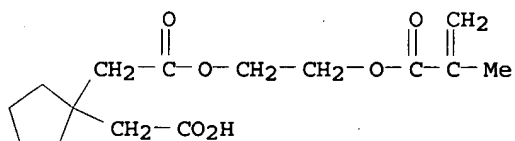
RN 676349-61-4 HCAPLUS

CN 1,1-Cyclopentanediadicetic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 2-propenamide and 2-propenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 393546-18-4

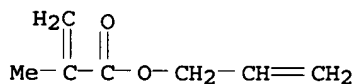
CMF C15 H22 O6



CM 2

CRN 96-05-9

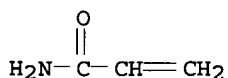
CMF C7 H10 O2



CM 3

CRN 79-06-1

CMF C3 H5 N O



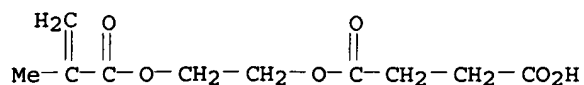
RN 676349-62-5 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-methyl-2-propenamide and 2-(2-propenyloxy)ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

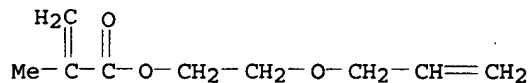
CMF C10 H14 O6



CM 2

CRN 16839-48-8

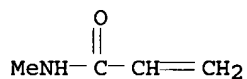
CMF C9 H14 O3



CM 3

CRN 1187-59-3

CMF C4 H7 N O



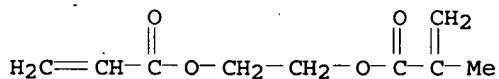
RN 676349-63-6 HCAPLUS

CN Butanedioic acid, mono[2-[(1-oxo-2-propenyl)oxy]ethyl] ester,
polymer with N,N-dimethyl-2-propenamide and 2-[(1-oxo-2-
propenyl)oxy]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 69040-48-8

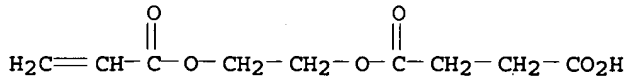
CMF C9 H12 O4



CM 2

CRN 50940-49-3

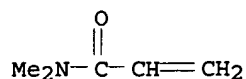
CMF C9 H12 O6



CM 3

CRN 2680-03-7

CMF C5 H9 N O



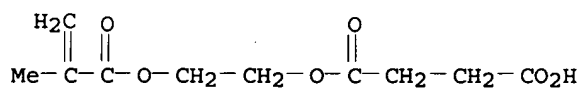
RN 676349-64-7 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-(1-methylethyl)-2-propenamide and 2-propenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

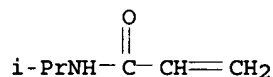
CMF C10 H14 O6



CM 2

CRN 2210-25-5

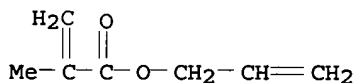
CMF C6 H11 N O



CM 3

CRN 96-05-9

CMF C7 H10 O2



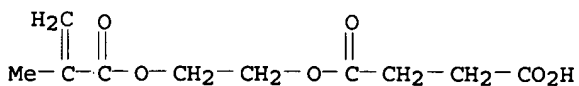
RN 676349-65-8 HCAPLUS

CN Butanedioic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 2-methyl-N-(1-methylethyl)-2-propenamide and 2-(2-propenyloxy)ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 20882-04-6

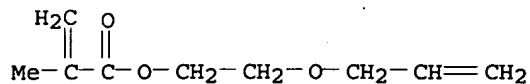
CMF C10 H14 O6



CM 2

CRN 16839-48-8

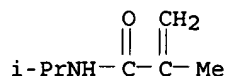
CMF C9 H14 O3



CM 3

CRN 13749-61-6

CMF C7 H13 N O



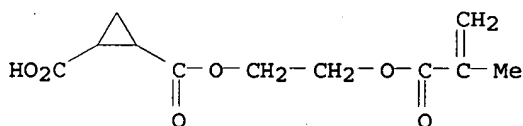
RN 676349-66-9 HCAPLUS

CM 1,2-Cyclopropanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-cyclohexyl-2-propenamide and 2-[(1-oxo-2-propenyl)amino]ethyl 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

CM 1

CRN 676349-40-9

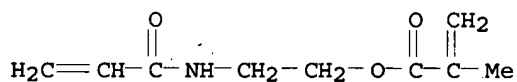
CMF C11 H14 O6



CM 2

CRN 56148-24-4

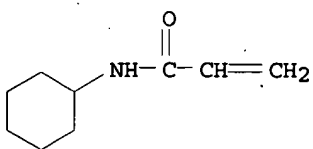
CMF C9 H13 N O3



CM 3

CRN 3066-72-6

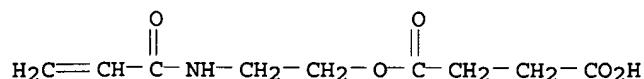
CMF C9 H15 N O



RN 676349-67-0 HCAPLUS
 CN Butanedioic acid, mono[2-[(1-oxo-2-propenyl)amino]ethyl] ester,
 polymer with 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 3-butenate and
 N-(phenylmethyl)-2-propenamide (9CI) (CA INDEX NAME)

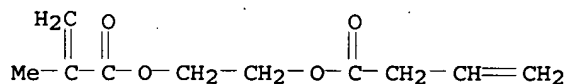
CM 1

CRN 159349-94-7
 CMF C9 H13 N O5



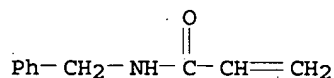
CM 2

CRN 127584-57-0
 CMF C10 H14 O4



CM 3

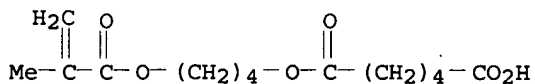
CRN 13304-62-6
 CMF C10 H11 N O



RN 676349-69-2 HCAPLUS
 CN Hexanedioic acid, mono[4-[(2-methyl-1-oxo-2-propenyl)oxy]butyl]
 ester, polymer with N-phenyl-2-propenamide and 2-propenyl
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

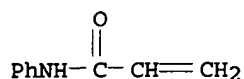
CM 1

CRN 676349-68-1
 CMF C14 H22 O6

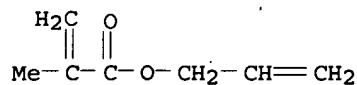


CM 2

CRN 2210-24-4
 CMF C9 H9 N O

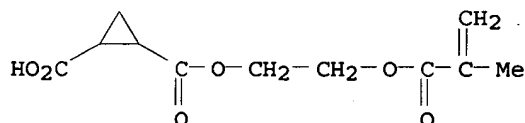


CM 3

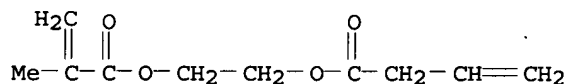
CRN 96-05-9
CMF C7 H10 O2

RN 676349-70-5 HCAPLUS
CN 1,2-Cyclopropanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N,N-di-2-propenyl-2-propenamide and 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl 3-butenate (9CI) (CA INDEX NAME)

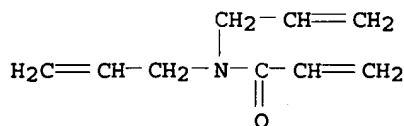
CM 1

CRN 676349-40-9
CMF C11 H14 O6

CM 2

CRN 127584-57-0
CMF C10 H14 O4

CM 3

CRN 3085-68-5
CMF C9 H13 N O

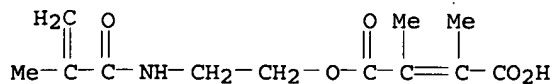
RN 676349-72-7 HCAPLUS
CN 2-Butenedioic acid, 2,3-dimethyl-, mono[2-[(2-methyl-1-oxo-2-propenyl)amino]ethyl] ester, polymer with N-cyclopentyl-2-

propenamide and 2-[(1-oxo-2-propenyl)oxy]ethyl 2-methyl-2-propenoate
(9CI) (CA INDEX NAME)

CM 1

CRN 676349-71-6

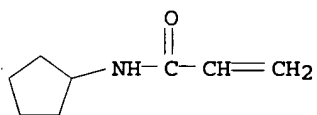
CMF C12 H17 N O5



CM 2

CRN 188026-02-0

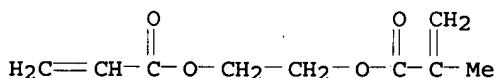
CMF C8 H13 N O



CM 3

CRN 69040-48-8

CMF C9 H12 O4



IC ICM B41C0001-10

ICS G03F0007-033

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST polymerizable compn **planog printing plate precursor**

IT **Printing plates**

(**planog.**; polymerizable composition and **planog.** printing plate precursor)

IT 658705-94-3 676349-35-2 676349-36-3

676349-37-4 676349-39-6 676349-41-0

676349-42-1 676349-43-2 676349-45-4 676349-47-6

676349-48-7 676349-51-2 676349-52-3 676349-54-5

676349-56-7 676349-57-8 676349-58-9

676349-59-0 676349-60-3 676349-61-4

676349-62-5 676349-63-6 676349-64-7

676349-65-8 676349-66-9 676349-67-0

676349-69-2 676349-70-5 676349-72-7

RL: PRP (Properties); TEM (Technical or engineered material use);

USES (Uses)

(polymerizable composition and **planog.** printing plate precursor)

IT 24504-22-1 120307-06-4 127820-39-7 253585-83-0 377780-83-1

676349-74-9 676349-76-1 676349-77-2 676349-78-3 676349-79-4

676349-80-7

RL: CAT (Catalyst use); USES (Uses)

(polymerization initiator; polymerizable composition and planog.
printing plate precursor)

L29 ANSWER 20 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 2004:118435 HCAPLUS
 DOCUMENT NUMBER: 140:190005
 TITLE: Light- or heat-sensitive image forming materials
 for lithographic printing plate
 precursors
 INVENTOR(S): Kunita, Kazuto
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 129 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004045626	A2	20040212	JP 2002-201433	200207 10
PRIORITY APPLN. INFO.:			JP 2002-201433	200207 10

AB The title material has a layer containing polymers having radically polymerizable groups of <1.5 mmol/g acid value and a polymer, which is alkali-solubilizable and has ≥1.5 mmol/g acid value and general structure -C(1)=C(R2)(R3) (R1-3 = H, hydrocarbon), on a support. The material shows high sensitivity and good storageability and is also suitable for other applications such as relief image forming, holog., color proof material, etc.

IT 658050-90-9P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (light- or heat-sensitive image forming materials for lithog.
 printing plate precursors)

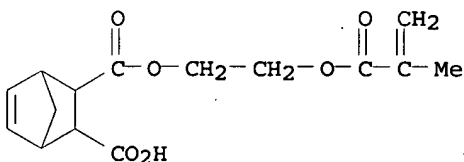
RN 658050-90-9 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2,3-dicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 64680-73-5

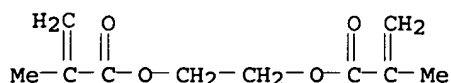
CMF C15 H18 O6



CM 2

CRN 97-90-5

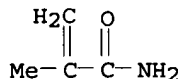
CMF C10 H14 O4



CM 3

CRN 79-39-0

CMF C4 H7 N O



IC ICM G03F0007-038
 ICS C08F0220-06; C08F0220-18; C08F0220-22; C08F0220-56;
 C08F0220-58; C08F0299-00; G03F0007-00; G03F0007-032
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and
 Other Reprographic Processes)
 ST light sensitive image lithog **printing plate**
precursor
 IT Lithographic plates
 (light- or heat-sensitive image forming materials for lithog.
printing plate precursors)
 IT Photoimaging materials
 (photopolymerizable; light- or heat-sensitive image forming
 materials for lithog. **printing plate precursors**
)
 IT Polymerization
 (thermal, imaging; light- or heat-sensitive image forming
 materials for lithog. **printing plate precursors**
)
 IT 49736-69-8P 90216-38-9P 133394-55-5P 657414-37-4P
 657414-38-5P 657414-39-6P 657414-40-9P 657414-44-3P
 657414-45-4P 657414-46-5P 657414-47-6P 657414-49-8P
 657414-50-1P 657414-51-2P **658050-90-9P** 658050-92-1P
 658050-93-2P 658050-94-3P 658050-95-4P 658050-96-5P
 658050-97-6P 658050-99-8P 658051-00-4P 658051-02-6P
 RL: SPN (Synthetic preparation); TEM (Technical or engineered
 material use); PREP (Preparation); USES (Uses)
 (light- or heat-sensitive image forming materials for lithog.
printing plate precursors)

L29 ANSWER 21 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2004:118434 HCAPLUS

DOCUMENT NUMBER: 140:190004

TITLE: Light- or heat-sensitive image forming materials
 for lithographic **printing plate**
precursors

INVENTOR(S): Kunita, Kazuto

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 124 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004045625	A2	20040212	JP 2002-201432	

Ross Shape EIC 1700 Remsen 4B31 571/272-6018

200207
10

PRIORITY APPLN. INFO.:

JP 2002-201432

200207
10

AB The title composition contains a polymer having radically polymerizable groups and a polymer alkali-solubilizable. The material shows high sensitivity and good storageability and is also suitable for other applications such as relief image forming, holog., color proof material, etc.

IT 657414-36-3P 657414-53-4P 657414-54-5P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polymers in light-sensitive image forming materials)

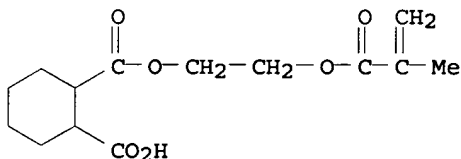
RN 657414-36-3 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1,2-ethanediyl bis(2-methyl-2-propenoate) and 2-methyl-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 51252-88-1

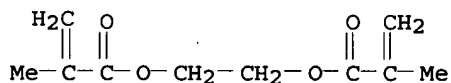
CMF C14 H20 O6



CM 2

CRN 97-90-5

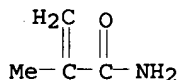
CMF C10 H14 O4



CM 3

CRN 79-39-0

CMF C4 H7 N O

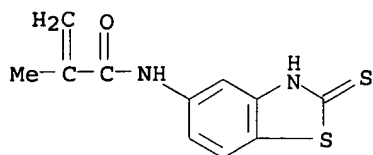


RN 657414-53-4 HCAPLUS

CN 1,2-Cyclohexanedicarboxylic acid, mono[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with N-(2,3-dihydro-2-thioxo-5-benzothiazolyl)-2-methyl-2-propenamide (9CI) (CA INDEX NAME)

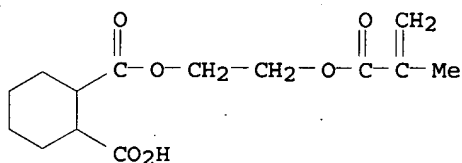
CM 1

CRN 110633-00-6
CMF C11 H10 N2 O S2



CM 2

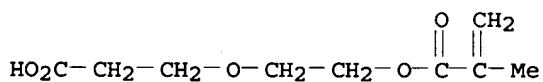
CRN 51252-88-1
CMF C14 H20 O6



RN 657414-54-5 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-(2-carboxyethoxy)ethyl ester, polymer with N-(2,3-dihydro-2-thioxo-5-benzothiazolyl)-2-methyl-2-propenamide (9CI) (CA INDEX NAME)

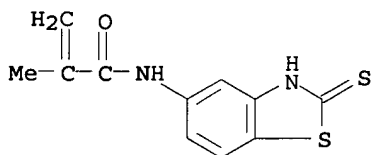
CM 1

CRN 196086-57-4
CMF C9 H14 O5



CM 2

CRN 110633-00-6
CMF C11 H10 N2 O S2



IC ICM G03F0007-032
ICS C08F0220-06; C08F0220-22; C08F0220-30; C08F0220-56;
C08F0299-00; G03F0007-00; G03F0007-038
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST light sensitive image lithog printing plate
precursor
IT Lithographic plates

(light- or heat-sensitive image forming materials for lithog. printing plate precursors)

IT Photoimaging materials
(photopolymerizable; light- or heat-sensitive image forming materials for lithog. printing plate precursors)

IT Polymerization
(thermal, imaging; light- or heat-sensitive image forming materials for lithog. printing plate precursors)

IT 49736-69-8P 146224-82-0P 223659-46-9P 657414-36-3P
657414-37-4P 657414-38-5P 657414-39-6P 657414-40-9P
657414-42-1P 657414-44-3P 657414-45-4P 657414-46-5P
657414-47-6P 657414-49-8P 657414-50-1P 657414-51-2P
657414-52-3P 657414-53-4P 657414-54-5P
657414-55-6P 657414-56-7P 657414-57-8P 657414-58-9P
657414-60-3P 657414-61-4P 657414-63-6P 657414-64-7P
657414-65-8P 657414-67-0P 657414-73-8P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polymers in light-sensitive image forming materials)

L29 ANSWER 22 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1999:633567 HCAPLUS

DOCUMENT NUMBER: 131:273246

TITLE: Oil-based inks for making printing plates by ink-jet printing method and their use in the formation of the plates

INVENTOR(S): Kato, Eiichi

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 35 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 11269416	A2	19991005	JP 1998-359379	19981217
US 6098545	A	20000808	US 1998-215837	19981217
PRIORITY APPLN. INFO.:			JP 1997-349737	A 19971218

AB The inks with good storage stability and printability are used on water-resistant lithog. printing plates which bear an image-receiving layer containing binding resins and ZnO and have a water contact angle of $\geq 30^\circ$, and contain dispersed resin particles (A) which are prepared by polymerizing monofunctional monomers with macromonomers and polymerizable dispersants having double bonds in a nonaq. medium having elec. resistance $\geq 109 \Omega \cdot \text{cm}$ and permittivity ≤ 3.5 . The plates are formed by ink-jet printing using the inks, and desensitizing the unprinted areas. Thus, a dispersion containing particles (A) was prepared by the 2,2'-azobis(isovaleronitrile)-initiated polymerization of vinyl acetate 100 with a macromonomer 4 in the presence of a polymerizable dispersant 10 g where the macromonomer was octadecyl methacrylate-3-mercaptopropionic acid telomer glycidyl methacrylate ester and the dispersant was an allyl ether of octadecyl methacrylate-4-(2-methacryloyloxyethyloxycarbonyl)butyric acid

copolymer. A plate precursor was coated with a mixture of ZnO 100, methacrylic acid-Me acrylate-Me methacrylate copolymer 3.0, acrylic acid-dodecyl acrylate-Me methacrylate-N-vinyl-2-pyrrolidone copolymer 17.0, benzoic acid 0.15 and PhMe 155 g to form a plate bearing an ink-receiving layer with water contact angle 102°. An ink composition was formed by shaking an acrylic acid-dodecyl methacrylate copolymer 10 with Alkali Blue 10 and Shellsol 71 30 in the presence of glass beads, then combined at 18 g with the particles (A) 50, and an octadecene-semi-maleic acid octadecylamide copolymer 0.09 g in 1 L Isopar G.

IT 220728-45-0P, 11-Methacrylamidoundecanoic acid-tridecyl methacrylate copolymer ester with vinyl acetate
 RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
 (reactive dispersant; manufacture of oil-based inks for making printing plates by ink-jet printing method and use in formation of plates)

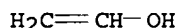
RN 220728-45-0 HCAPLUS

CN Undecanoic acid, 11-[(2-methyl-1-oxo-2-propenyl)amino]-, polymer with tridecyl 2-methyl-2-propenoate, ethenyl ester (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5

CMF C2 H4 O



CM 2

CRN 220728-44-9

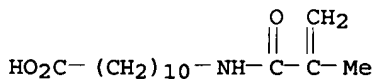
CMF (C17 H32 O2 . C15 H27 N O3)x

CCI PMS

CM 3

CRN 59178-93-7

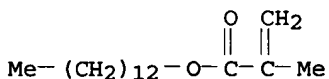
CMF C15 H27 N O3



CM 4

CRN 2495-25-2

CMF C17 H32 O2



IC ICM C09D0011-00

ICS B41C0001-10; B41J0002-01; B41N0001-14

CC 42-11 (Coatings, Inks, and Related Products)
 Section cross-reference(s): 74

ST ink jet printing plate manuf oil based ink; macromonomer

- vinyl copolymer dispersion oil based ink; reactive dispersant binder
oil based ink **printing** plate; lithog **printing**
plate manuf ink jet ink
- IT Isoalkanes
RL: NUU (Other use, unclassified); USES (Uses)
(C9-12, Isopar G, Isopar H, ink medium; manufacture of oil-based inks
for making **printing** plates by ink-jet **printing**
method and use in formation of plates)
- IT Inks
(jet-**printing**; oil-based inks for making
printing plates by ink-jet **printing** method and
use in formation of plates)
- IT Macromonomers
RL: IMF (Industrial manufacture); RCT (Reactant); PREP
(Preparation); RACT (Reactant or reagent)
(manufacture of oil-based inks for making **printing** plates by
ink-jet **printing** method and use in formation of plates)
- IT Ink-jet **printing**
Lithographic plates
(oil-based inks for making **printing** plates by ink-jet
printing method and use in formation of plates)
- IT Dispersing agents
(reactive; in manufacture of oil-based inks for making
printing plates by ink-jet **printing** method and
use in formation of plates)
- IT 245492-45-9, Octadecyl vinyl ether-maleic monooctadecylamide
copolymer 245669-01-6, Octadecene-maleic monooctadecylamide
copolymer
RL: POF (Polymer in formulation); TEM (Technical or engineered
material use); USES (Uses)
(co-binder; manufacture of oil-based inks for making **printing**
plates by ink-jet **printing** method and use in formation
of plates)
- IT 25719-52-2, Dodecyl methacrylate polymer 28062-60-4, Acrylic
acid-dodecyl methacrylate copolymer
RL: TEM (Technical or engineered material use); USES (Uses)
(ink co-binder; manufacture of oil-based inks for making
printing plates by ink-jet **printing** method and
use in formation of plates)
- IT 2580-56-5, Victoria Blue B
RL: TEM (Technical or engineered material use); USES (Uses)
(ink color; manufacture of oil-based inks for making **printing**
plates by ink-jet **printing** method and use in formation
of plates)
- IT 8005-03-6, Nigrosine 68993-80-6, Alkali Blue
RL: TEM (Technical or engineered material use); USES (Uses)
(ink composition; manufacture of oil-based inks for making **printing**
plates by ink-jet **printing** method and use in formation
of plates)
- IT 245492-19-7 245492-20-0 245492-21-1 245492-22-2 245492-24-4
245492-25-5
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical
or engineered material use); USES (Uses)
(latex binder; manufacture of oil-based inks for making
printing plates by ink-jet **printing** method and
use in formation of plates)
- IT 106-91-2DP, Glycidyl methacrylate, ester with carboxy-terminated
dihexanoyloxypropyl methacrylate polymer 138005-14-8DP,
2,3-Dihexanoyloxypropyl methacrylate homopolymer,
carboxy-terminated, ester with glycidyl methacrylate 139104-87-3P
139104-90-8P 139105-03-6P 139105-08-1P, Octadecyl
methacrylate-3-mercaptopropionic acid telomer glycidyl methacrylate
ester 139105-12-7P 147130-31-2P 147130-40-3P 147130-42-5P
147130-44-7P 147130-50-5P 214835-07-1P 215877-54-6P,
Tetradecyl methacrylate-thioethanol telomer ester with
2-carboxyethyl acrylate 215877-61-5P 215877-71-7P 217188-65-3P

RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(macromonomers; manufacture of oil-based inks for making **printing plates by ink-jet printing method and use in formation of plates**)

IT 245492-26-6 245492-27-7 245492-29-9 245492-30-2 245492-31-3
245492-32-4 245492-34-6 245492-35-7 245492-36-8 245492-39-1
245492-41-5 245492-42-6 245492-44-8

RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(manufacture of oil-based inks for making **printing plates by ink-jet printing method and use in formation of plates**)

IT 104922-28-3P, Octadecyl methacrylate-4-(2-methacryloyloxyethyloxycarbonyl)butyric acid copolymer allyl ester **220728-45-0P**, 11-Methacrylamidoundecanoic acid-tridecyl methacrylate copolymer ester with vinyl acetate 220728-51-8P 221654-03-1P, Dodecyl methacrylate-octadecyl acrylate-glycidyl methacrylate copolymer ester with 3-acryloyloxypropionic acid

RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(reactive dispersant; manufacture of oil-based inks for making **printing plates by ink-jet printing method and use in formation of plates**)

IT 26936-24-3, Methacrylic acid-methyl acrylate-methyl methacrylate copolymer 27233-87-0, Methyl acrylate-methyl methacrylate-styrene copolymer 60472-57-3, Methacrylic acid-methyl acrylate-methyl methacrylate-styrene copolymer 184970-55-6, Acrylic acid-dodecyl acrylate-methyl methacrylate-N-vinyl-2-pyrrolidone copolymer 245492-46-0, Acrylic acid-N-methylacrylamide-methyl acrylate-methyl methacrylate copolymer 245492-47-1, Acrylic acid-Macromonomer AA 6-ethylene glycol dimethacrylate graft copolymer

RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(receiving layer composition; manufacture of oil-based inks for making **printing plates by ink-jet printing method and use in formation of plates**)

IT 1314-13-2, Zinc oxide, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(receiving layer composition; manufacture of oil-based inks for making **printing plates by ink-jet printing method and use in formation of plates**)

L29 ANSWER 23 OF 23 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1997:692363 HCAPLUS

DOCUMENT NUMBER: 128:17344

TITLE: Photosensitive material useful in production of **printing plate and color proof**

INVENTOR(S): Sakurai, Seiya; Yamanochi, Junichi; Shirato, Kentaro; Arai, Tsutomu

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 26 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 09274321	A2	1997.10.21	JP 1996-106304	1996.04.03

PRIORITY APPLN. INFO.: JP 1996-106304

1996.04.03

1996.04.03

AB In the title material which comprises a support coated with a peeling-promoting layer, a curing layer containing polymerizing compds. or crosslinking polymers, and a Ag halide-containing photosensitive layer, contains reducing agents, and is used in an imaging process involving the steps of imagewise exposing the material, heat-treating to make the cured and uncured areas corresponding to the exposed and unexposed areas, resp., into the curing layer, and peeling the uncured area of the layer off together with the photosensitive layer from the support and peeling-promoting layer to form a residual images made of the cured area on the support, the peeling-promoting or curing layer contains a copolymer having repeating units CR1R2CR3R4 and CH2CR11R12 (I) (R1, R2 = H, F; R3 = H, F, C1-4 (F-substituted) alkyl; R4 = monovalent group having ≥ 1 F; R11 = H, halo, C1-4 alkyl; R12 = monovalent group having ≥ 1 hydrophilic group). The copolymer may have repeating units I and CH2CR5R6 (R5 = H, C1-4 alkyl; R6 = C ≥ 7 saturated aliphatic hydrocarbon, C ≥ 7 arom hydrocarbon, monovalent group having ≥ 1 group composed of saturated aliphatic hydrocarbon and aromatic hydrocarbon groups which combine). The material useful in production of **printing** plates and color proofs provides clear images with high mech. strength. Thus, a PET film was coated successively with a peeling-promoting layer containing copolymer [CH2CMe(CO2CH2(CF2)8H)]35[CH2CH(CO2H)]65 (II) and dipentaerythritol hexaacrylate (III), a curing layer containing II, III, and a pigment, an intermediate layer, a photosensitive AgBr emulsion layer containing a reducing agent, and an overcoat layer containing a base precursor to give a photosensitive sheet.

IT 198835-72-2

RL: DEV (Device component use); USES (Uses)
(photopolymn. imaging composition with peeling-promoting layer or curing layer containing fluoropolymer or hydrocarbon polymer)

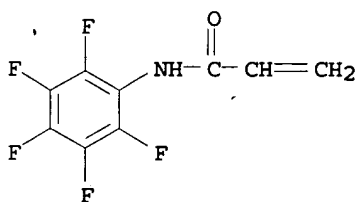
RN 198835-72-2 HCAPLUS

CN Heptanoic acid, 7-[(1-oxo-2-propenyl)oxy]-, polymer with N-(pentafluorophenyl)-2-propenamide (9CI) (CA INDEX NAME)

CM 1

CRN 198835-71-1

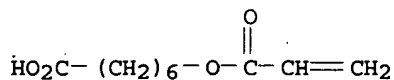
CMF C9 H4 F5 N O



CM 2

CRN 154707-74-1

CMF C10 H16 O4



IC ICM G03F0007-06

ICS G03F0003-10; G03F0007-00; G03F0007-004; G03F0007-027;

G03F0007-11

CC 74-4 (Radiation Chemistry, Photochemistry, and Photographic and
Other Reprographic Processes)
IT 28062-60-4, Acrylic acid-dodecyl methacrylate copolymer 35641-59-9
53058-84-7 127991-65-5 198835-70-0 198835-72-2
198835-73-3 198835-74-4 199011-59-1
RL: DEV (Device component use); USES (Uses)
(photopolymn. imaging composition with peeling-promoting layer or
curing layer containing fluoropolymer or hydrocarbon polymer)

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